

# MOTH-EYE ANTIREFLECTION FOR SMALL SATELLITES

SMALL SAT CONFERENCE 08/11/15  
HUGH PODMORE  
REGINA LEE

creative

passionate

rational

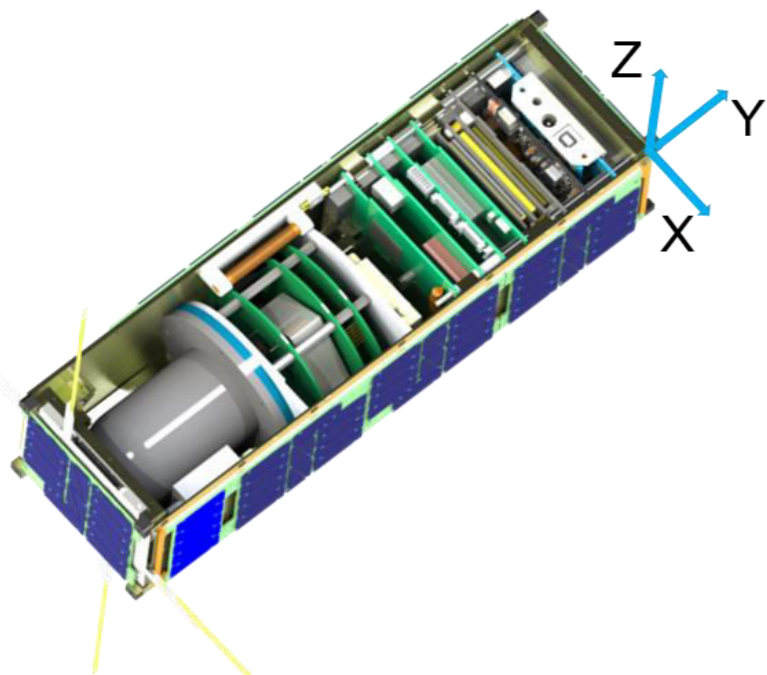
confident

ingenious

# OUTLINE

- Introduction to Moth-Eye Antireflection (MEAR)
- Design and Fabrication of MEAR surfaces for CubeSats
- Characterization of MEAR surface and implications for CubeSats
- Conclusions, contributions and future work

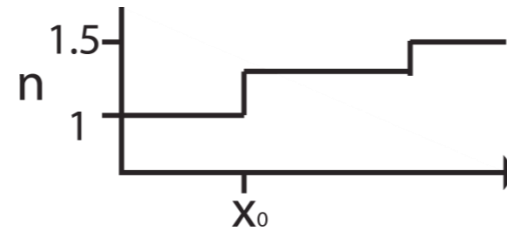
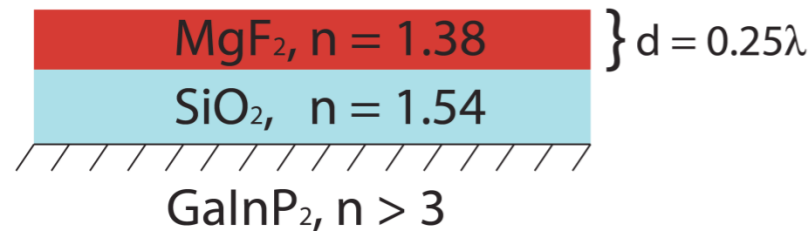
# MEAR FOR CUBESATS



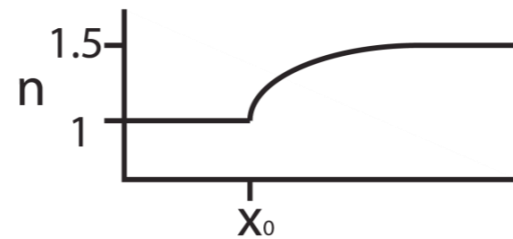
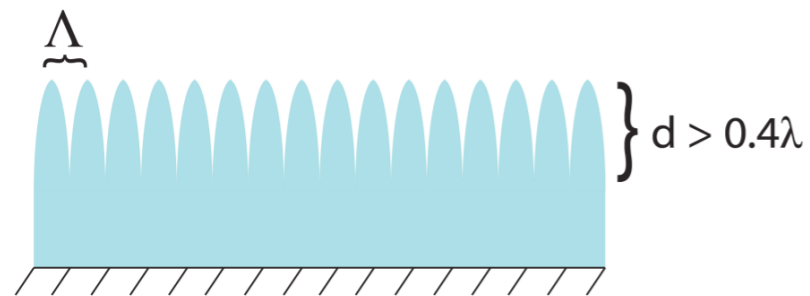
CAD model of 3-U SIGMA CubeSat  
operated by Kyung-Hee University

- High-quality science requires large power budgets.
- CubeSat volume constrains power:
  - Small surface area for light collection
  - Adding arrays possible, but difficult
  - Small surface, high incidence
- Many CubeSats adhere their own coverglass. Can this glass be improved to increase transmission at high angles of incidence?

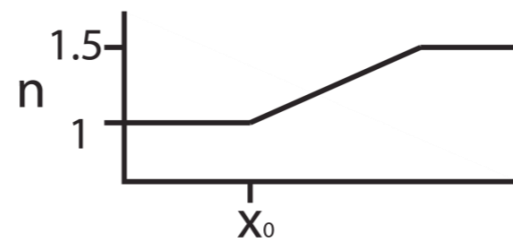
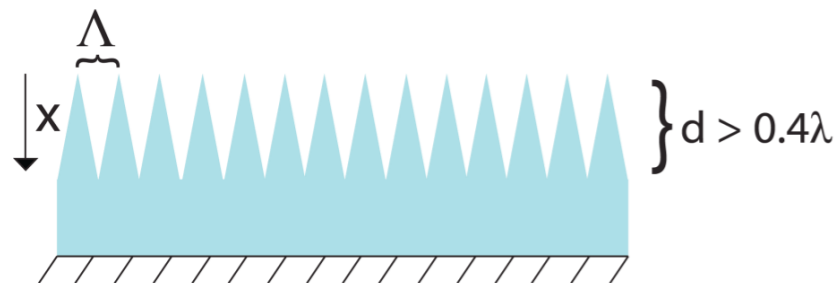
# MEAR THEORY



- Components 180° out of phase
- Interference reduces impedance

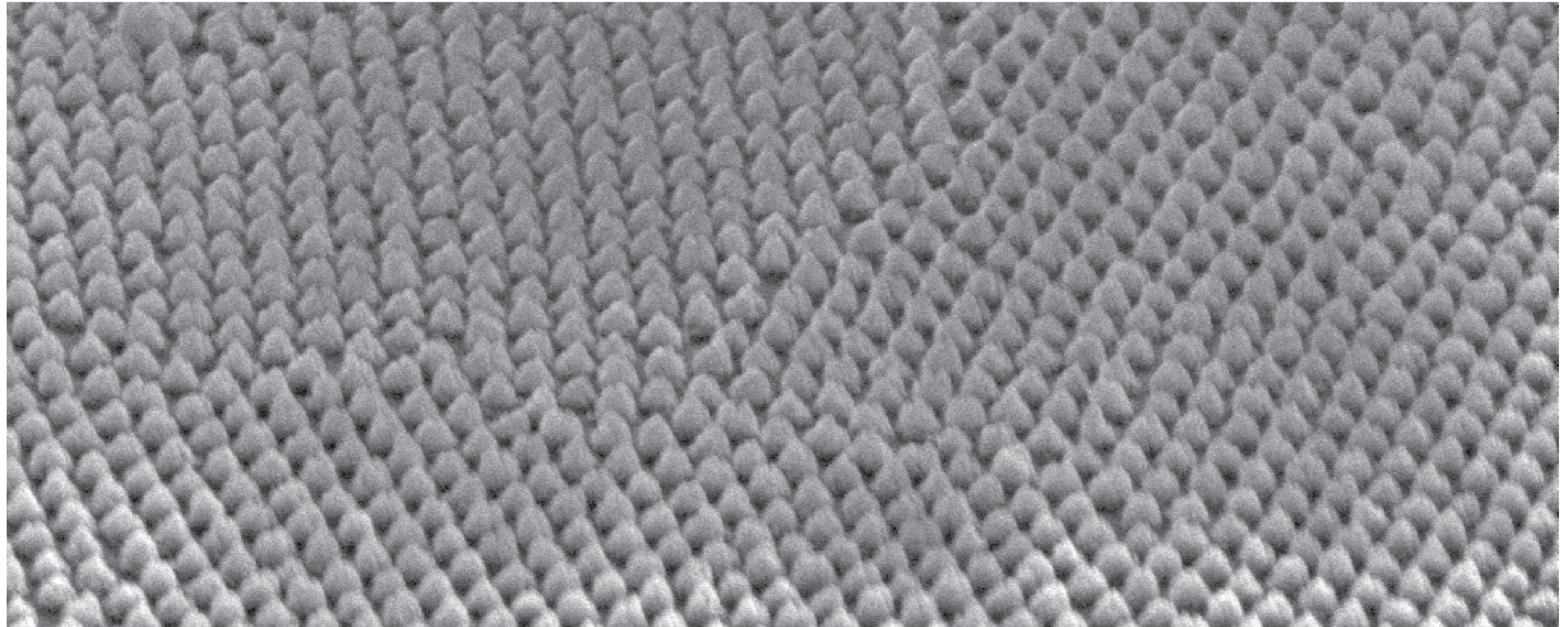


- Infinite boundaries → Infinite reflections
- Infinite reflections → Total destructive interference





# MEAR THEORY



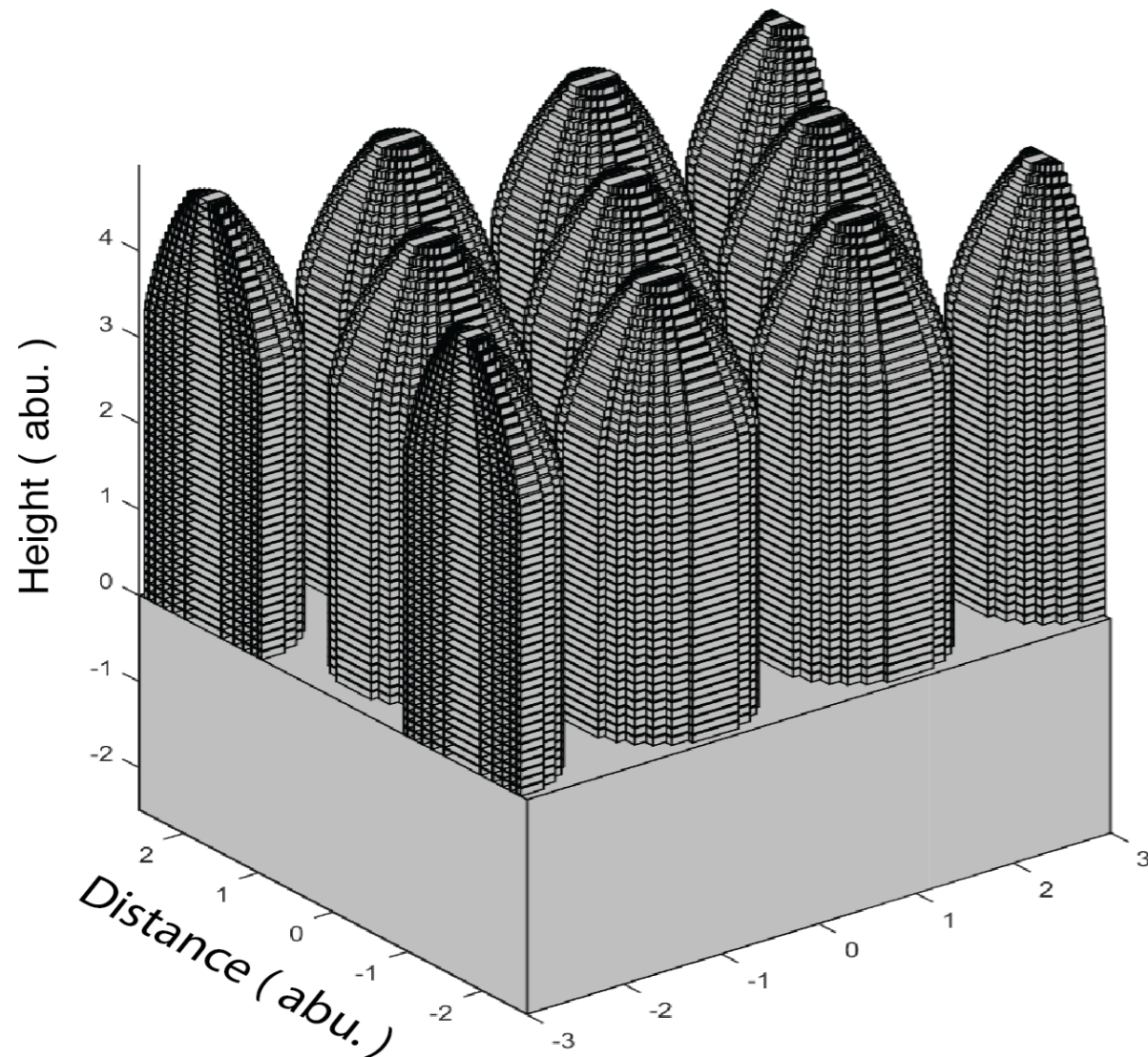
	HV 10.00 kV	det ETD	WD 10.0 mm	mag $\boxtimes$ 24 997 x	HFV 5.97 $\mu\text{m}$	pressure 6.60e-6 Torr	$\longleftrightarrow$ 1 $\mu\text{m}$ $\longleftrightarrow$ Quanta 3D FEG
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# MEAR THEORY

- Nanostructured surfaces reduce reflection by subwavelength antireflection (MEAR-effect)
- MEAR conditions:
  - Maximum pitch:  $\Lambda < \lambda_{\min}/2n$
  - Minimum height:  $h > 0.4 \lambda_{\max}$
- Profile is important: index changes as a function of the fill factor.
  - “Klopfenstein tapers” (5-th order poly, sine curve) are ideal but not necessary provided index is graded
- MEAR surfaces provide strong antireflection even at high incidence

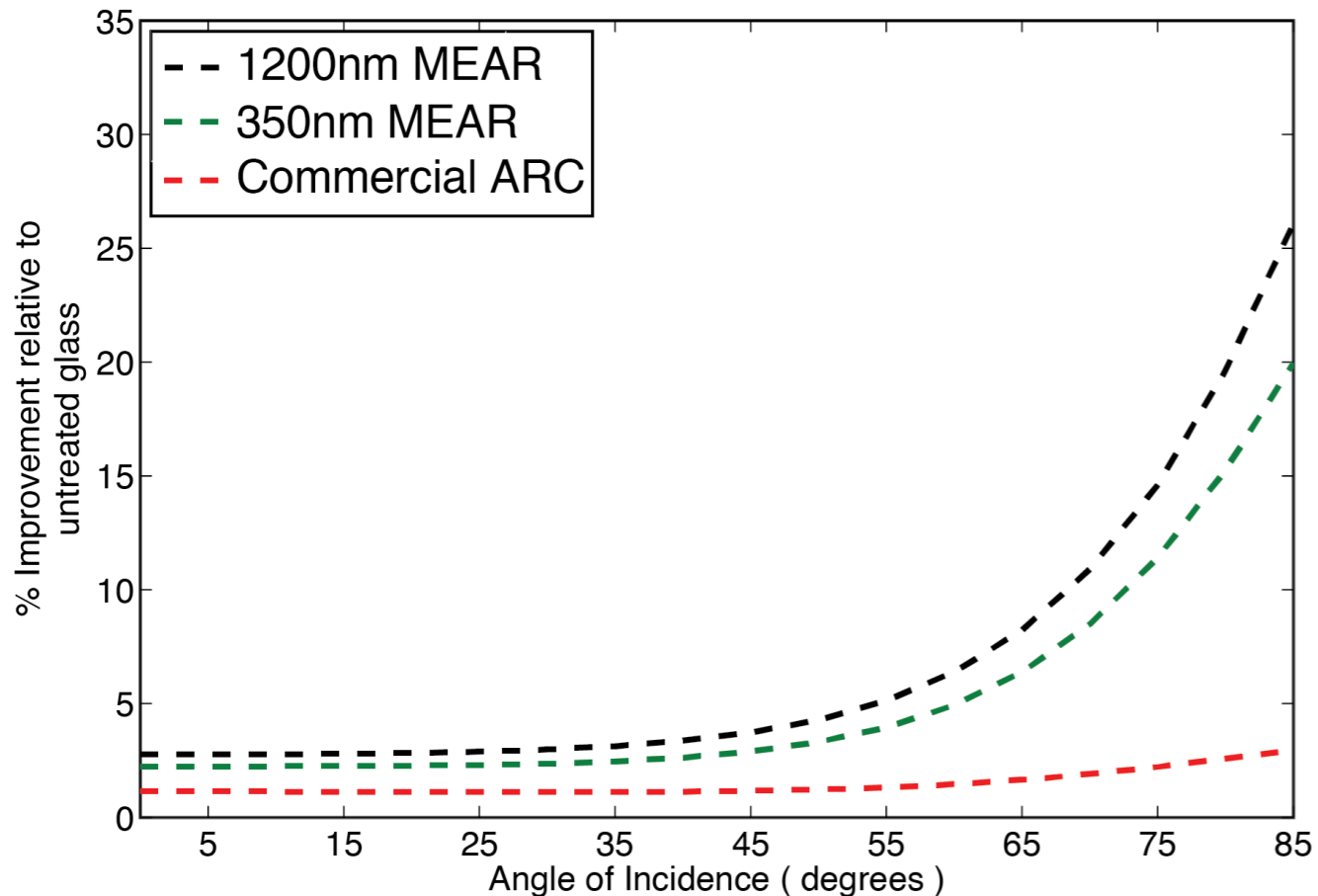


# MOTH EYE DESIGN



- Simulate transmission using Rigorous Coupled Wave Analysis (RCWA)
  - GD-CALC, MPB, S<sup>4</sup>
- Determine transmittance
- Convolve with EQE & Spectra, integrate across wavelength to get  $P(\theta)$
- Comparison with attitude data yields power production

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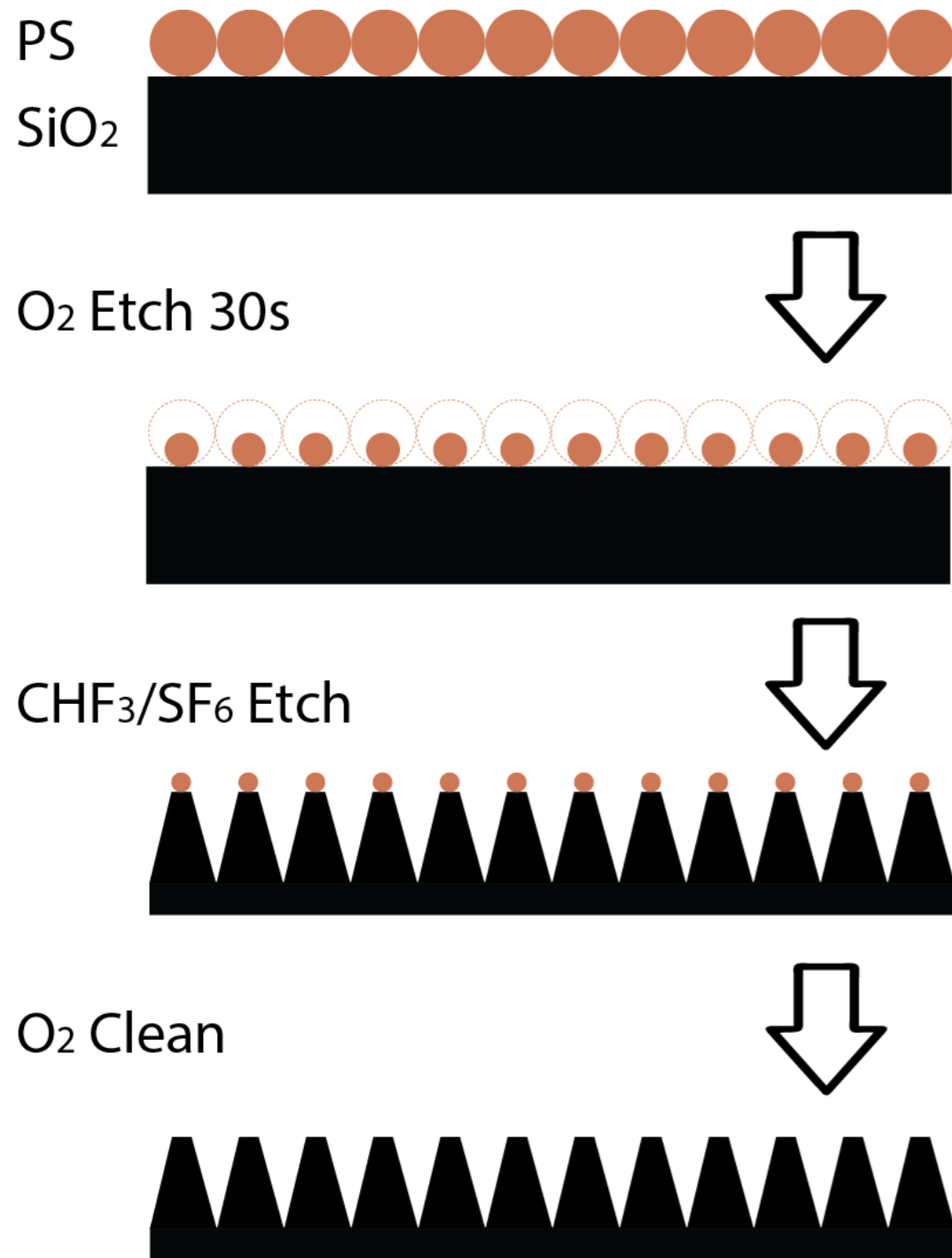
# MOTH EYE FABRICATION OBJECTIVES

- Feature height,
  - EMT-TMM suggests diminishing returns at  $h > 500\text{nm}$
  - RCWA optimization gives  $h = 1204\text{nm}$
- Spacing  $\Lambda < 150\text{nm}$
- Pyramidal or 5<sup>th</sup> order polynomial profile

## REALITY

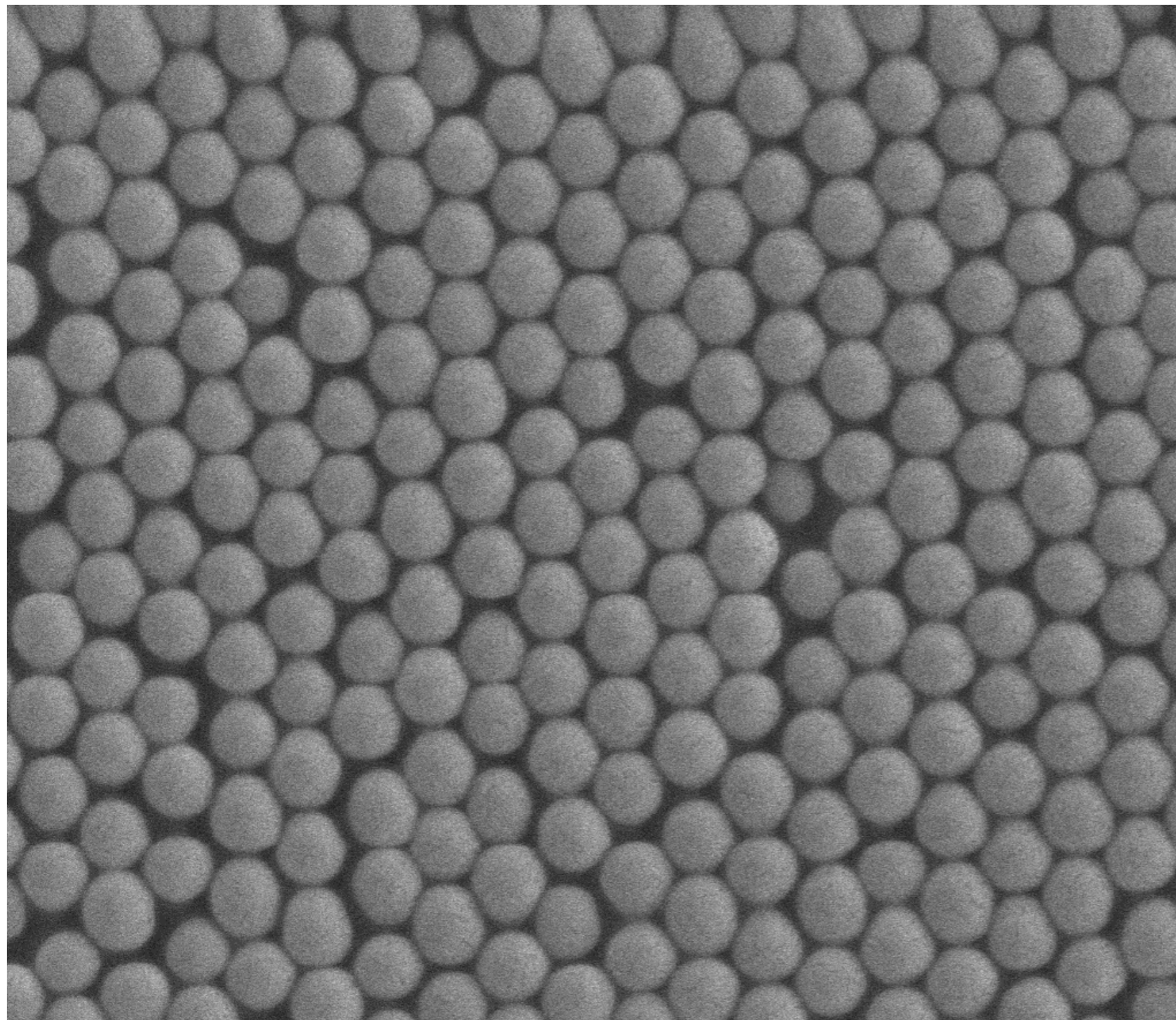
- Feature height, spacing and profile highly dependent on fabrication process
- “You can’t coat a CubeSat in gold.”

# MOTH EYE FABRICATION



- Nanosphere Lithography (NSL)
- Assembly of etch mask by colloidal self-assembly
- RIE in CHF<sub>3</sub>/SF<sub>6</sub> Plasma
- Etch mask made of PS Nanospheres
- Cheap & Simple, produces aspect ratio 5:1

# NANOSPHERE LITHOGRAPHY

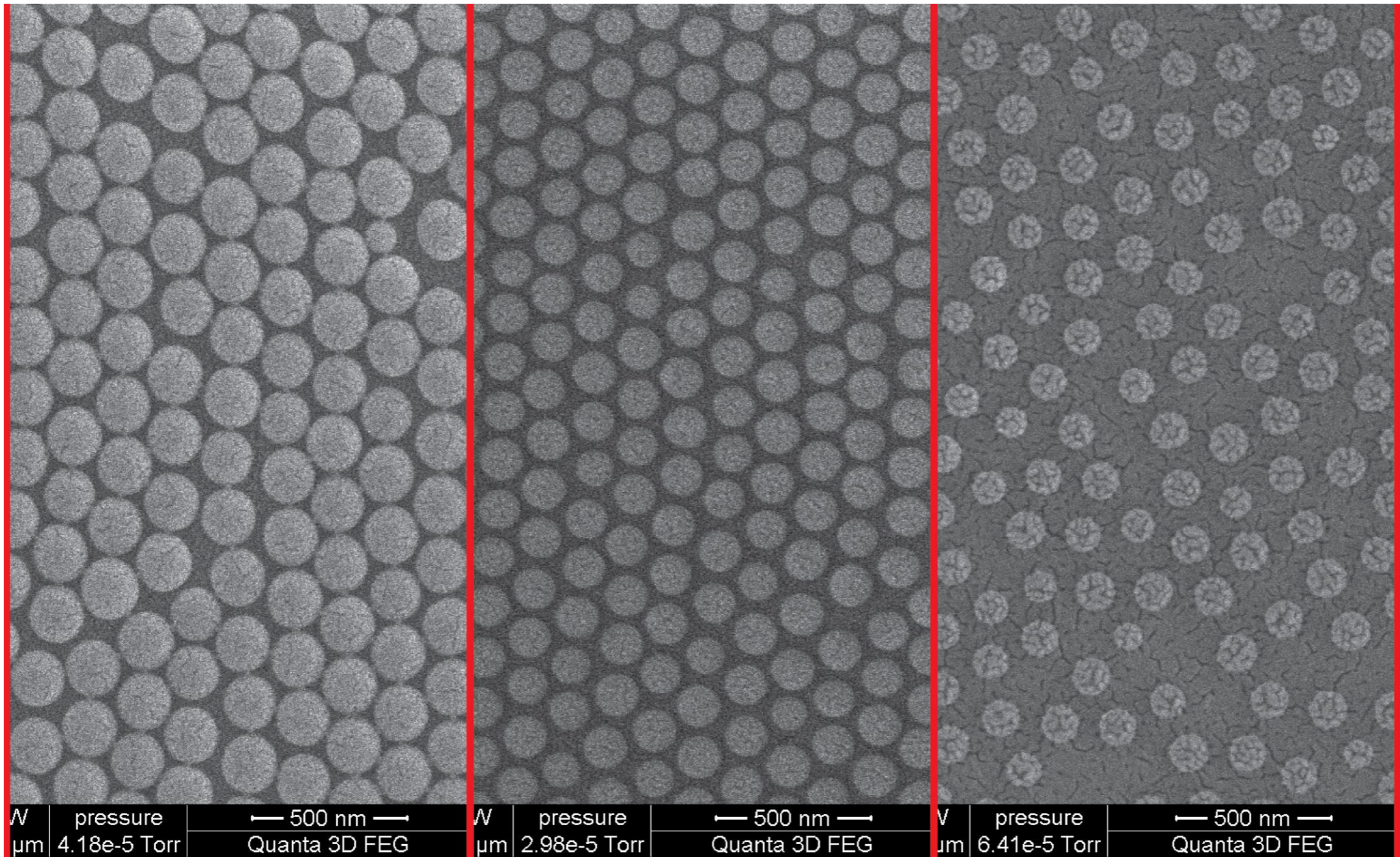


- Produces monolayer in hexagonally close packed (HCP) configuration.
- Defects at small scale due to particle size.

HV 10.00 kV | det ETD | WD 9.9 mm | mag 50 000 x | HFW 2.98  $\mu$ m | pressure 2.23e-5 Torr | — 500 nm — | Quanta 3D FEG



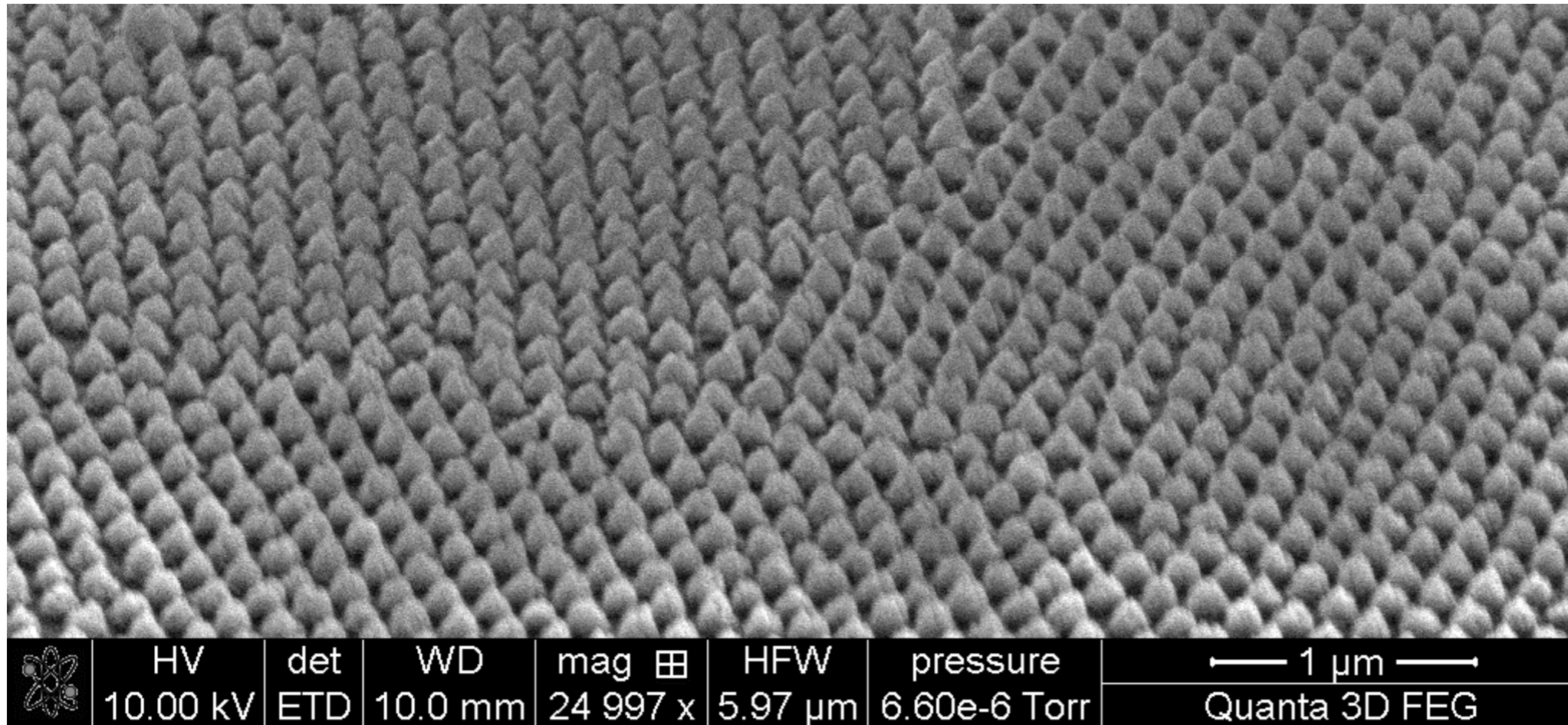
# SIZE REDUCTION



15s, 30s, 45s



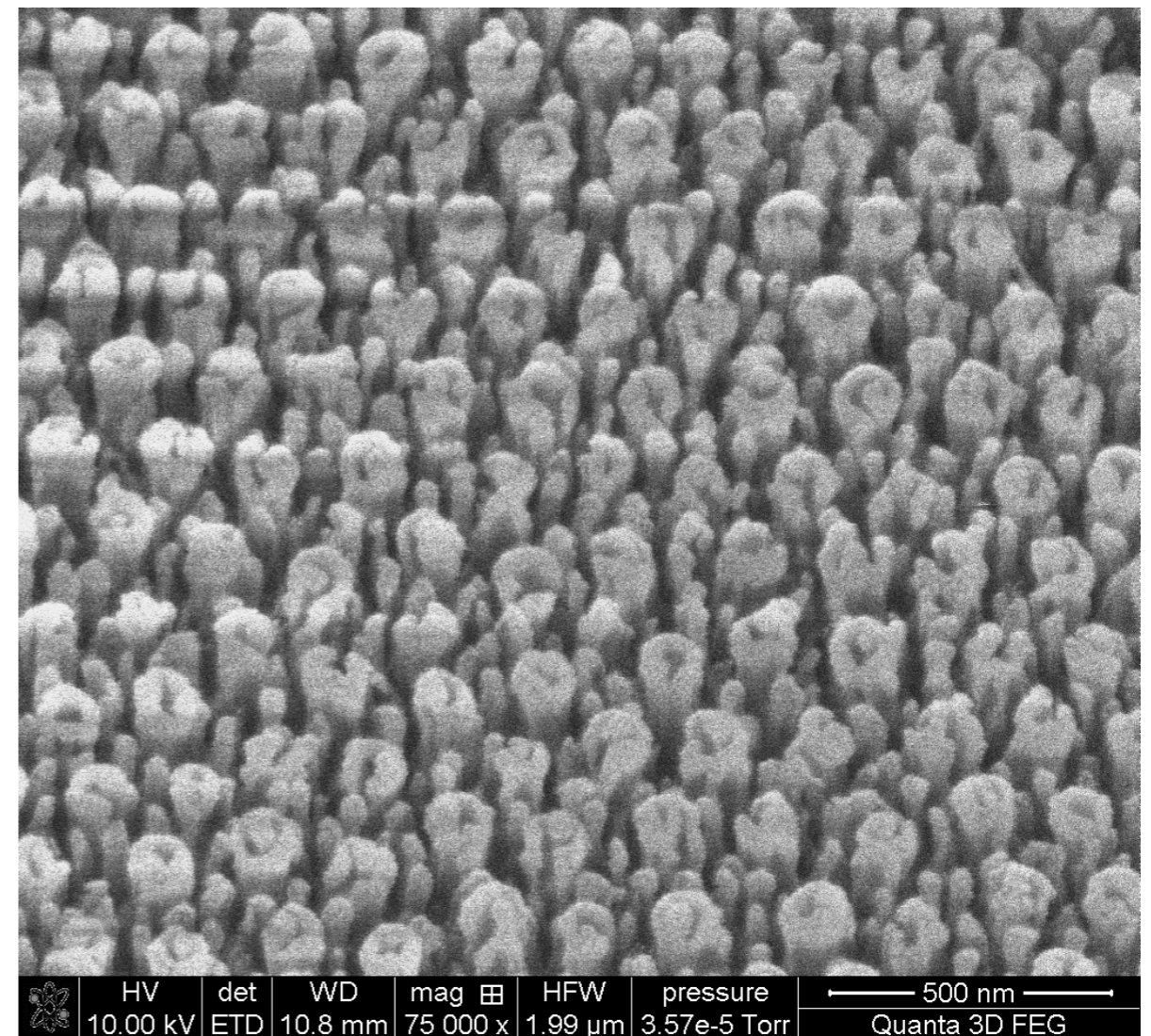
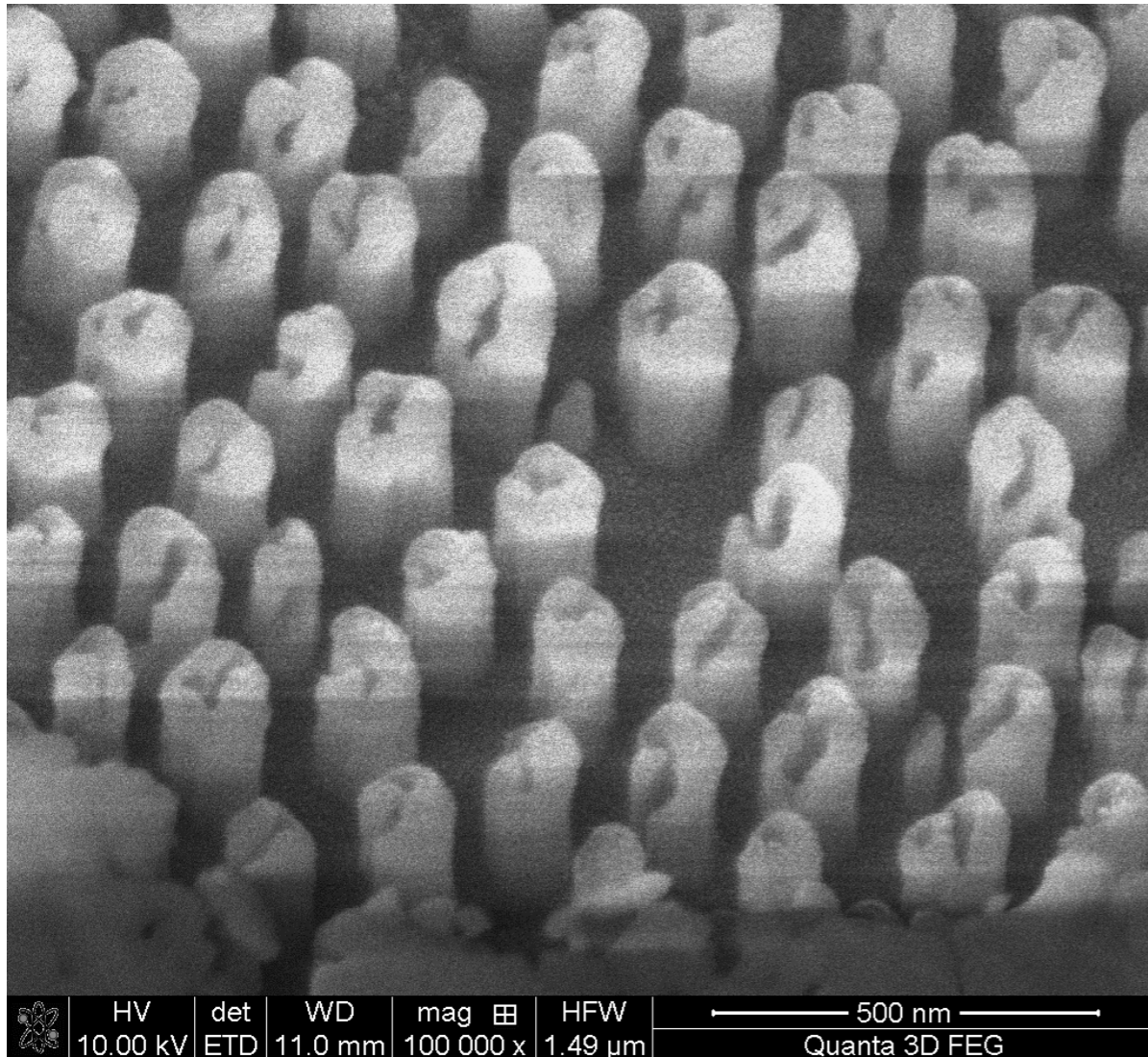
# RIE ETCHING



- Previously obtained well-ordered structures, unable to achieve high aspect ratios



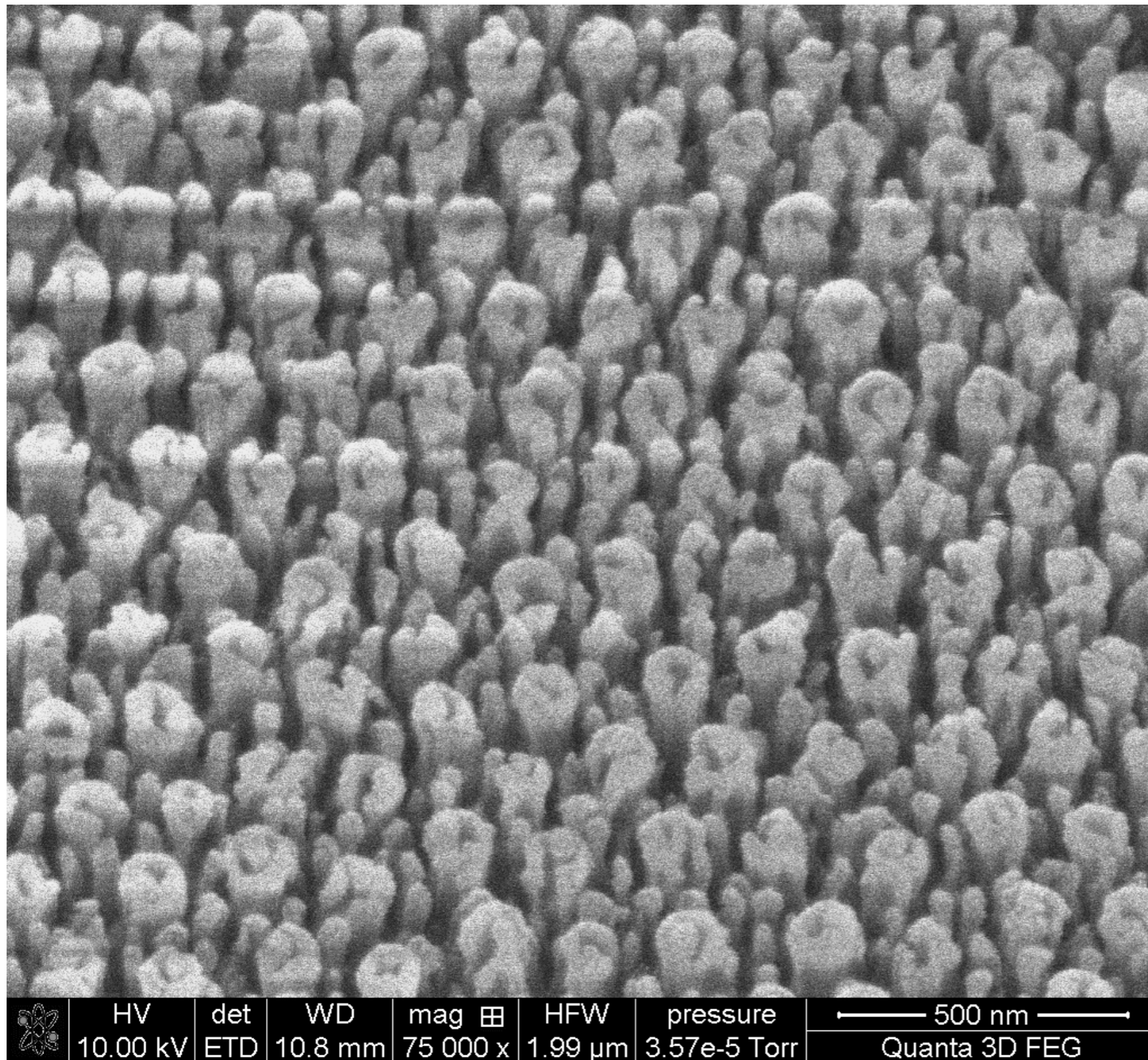
# RIE ETCHING



- More recently obtained higher aspect ratio structures.
- Structures ordered with inter-particle columns



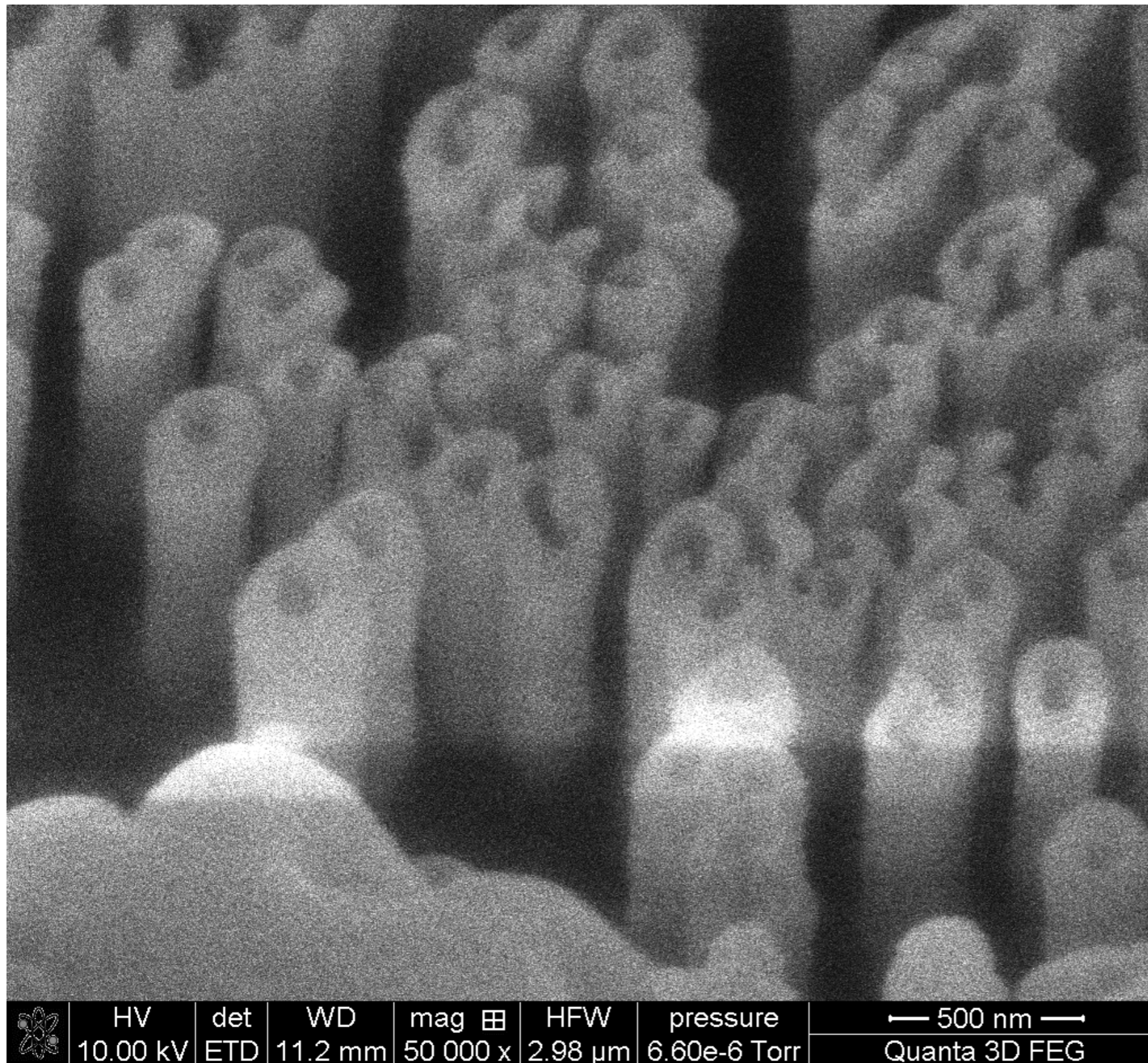
# RIE ETCHING



- Inter-particle structures the result of micromasking
- “RIE-Grass” or Glass grass
- MEAR structures with no mask?



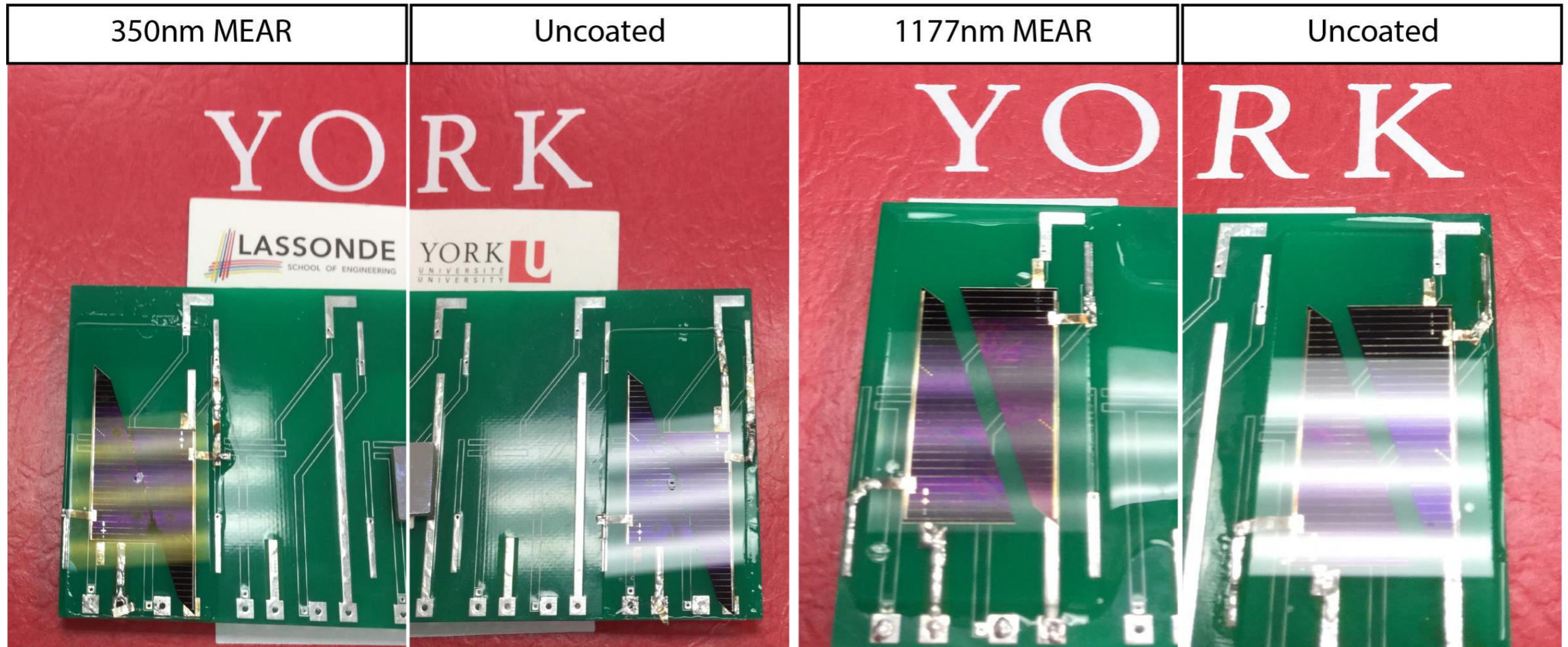
# RIE ETCHING



- 1177nm height
- Spacing 130nm
- Tube-like appearance consistent with literature
- Do these structures exhibit MEAR?



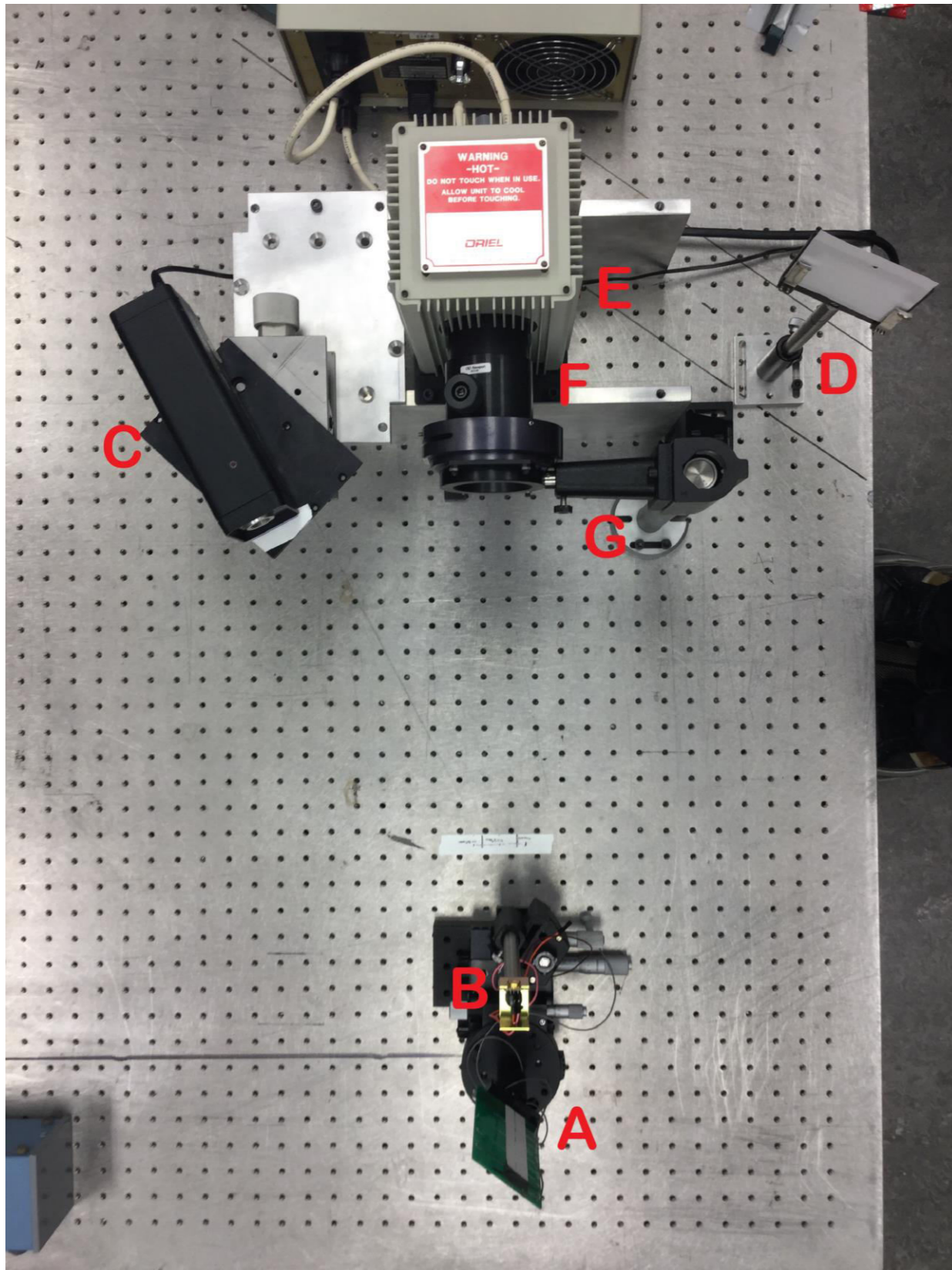
# TESTING AND CHARACTERIZATION



- Left – NSL Fabrication
- Right – Maskless, single step fabrication



# TESTING AND CHARACTERIZATION



A) Solar cell panel on rotator & translators.

B) Beam power sensor

C) Alignment laser

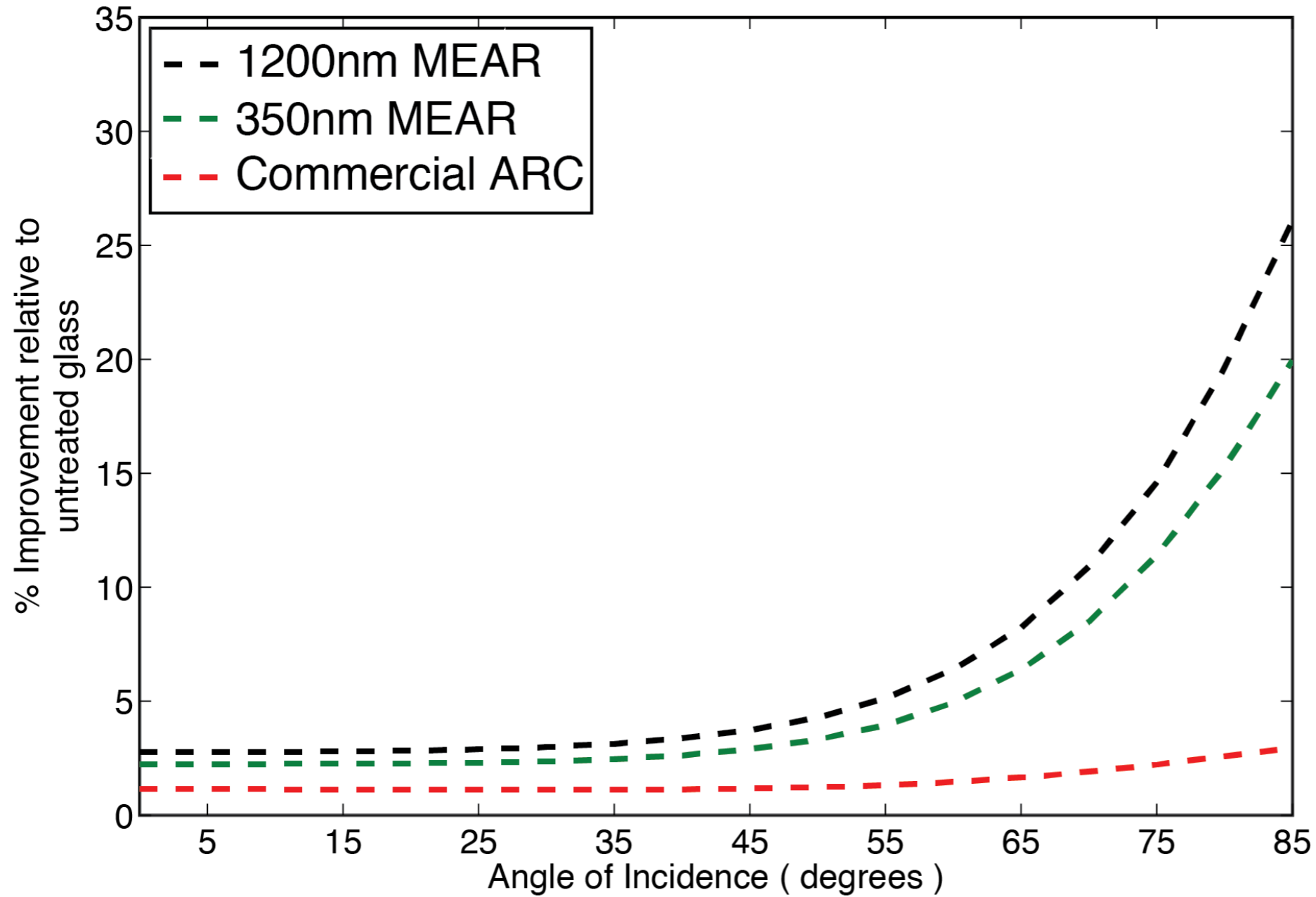
D) Imaging screen

E) 75W Xenon arc lamp

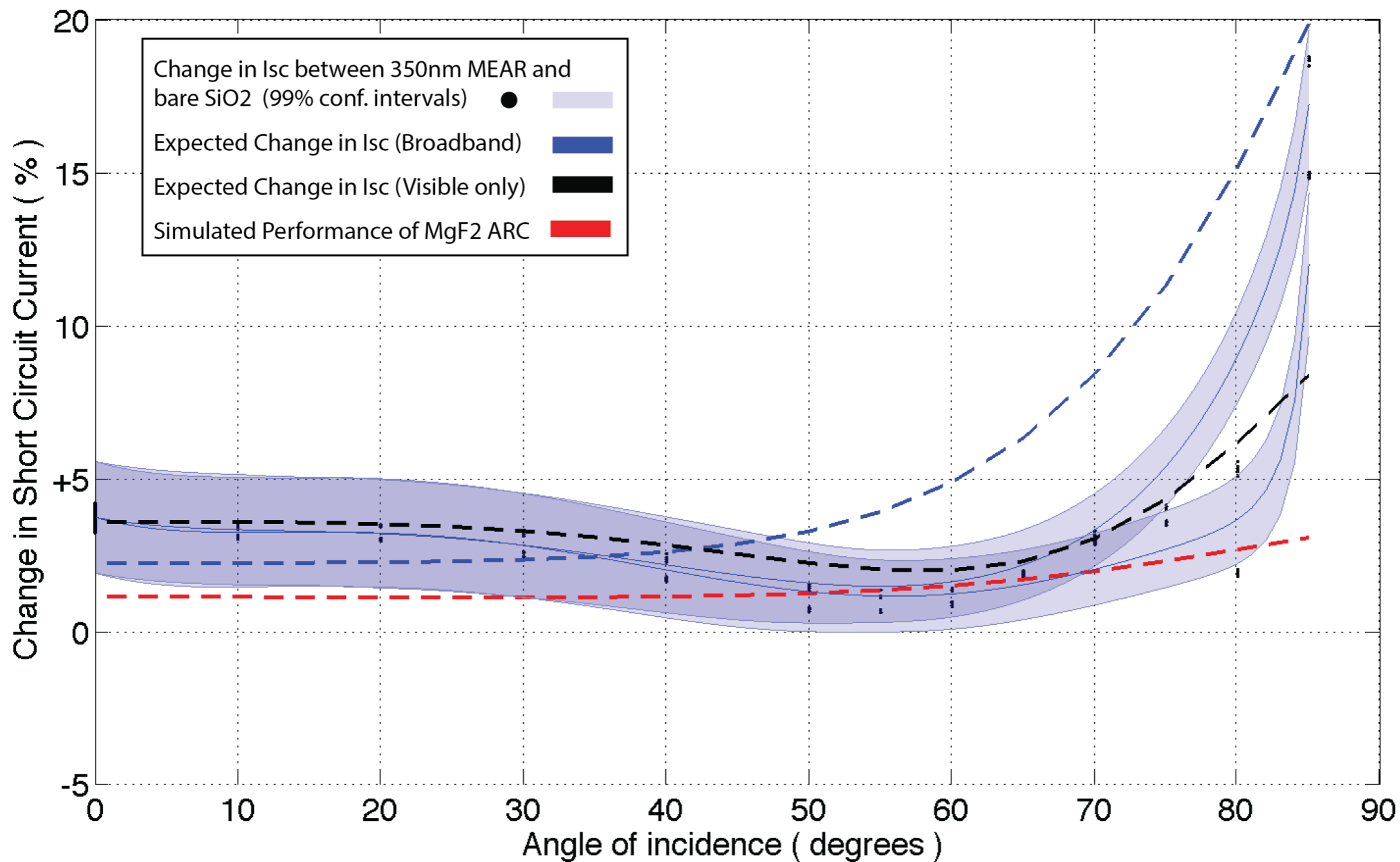
F) 33mm diameter collimator

G) Shutter

# TESTING AND CHARACTERIZATION



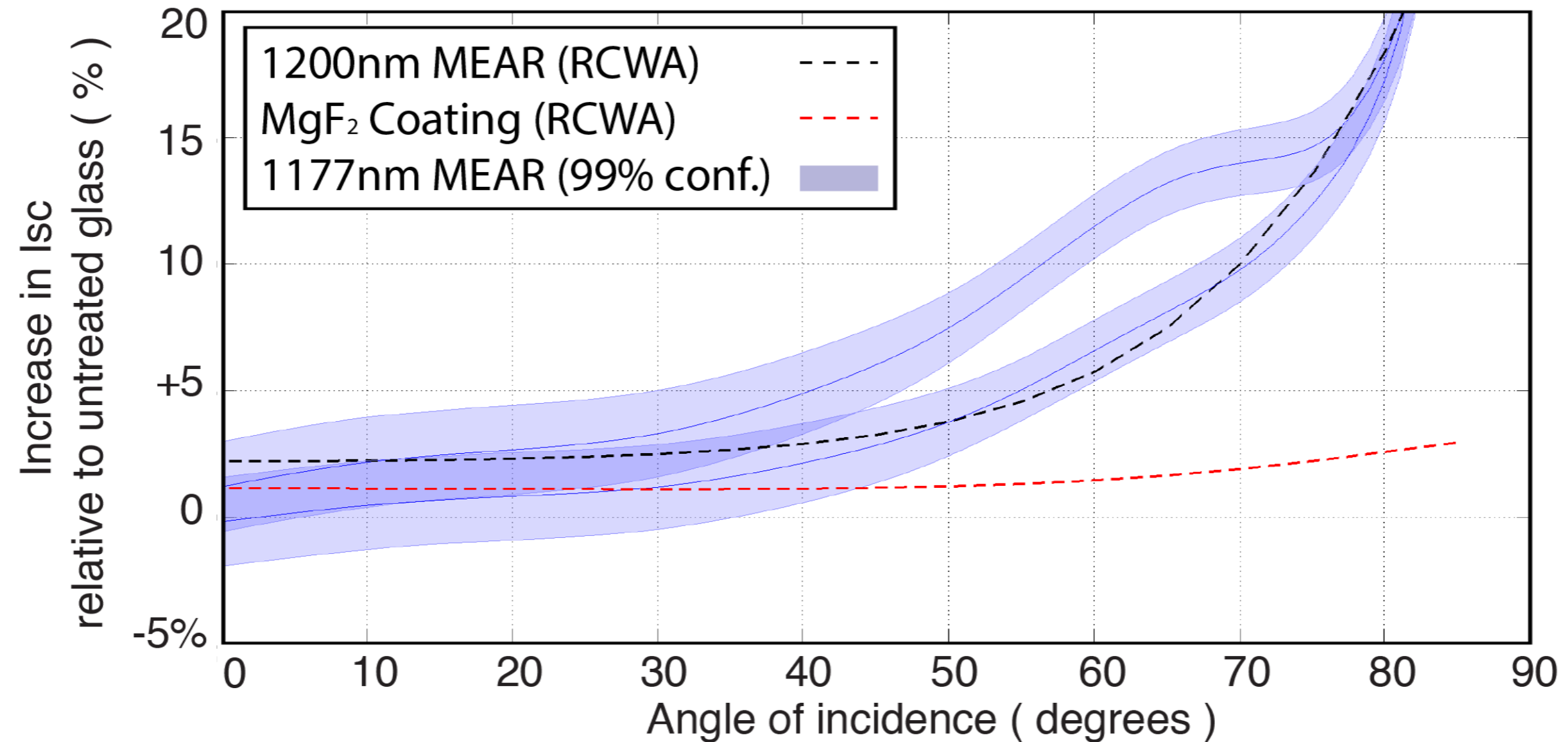
# TESTING AND CHARACTERIZATION



- 350nm MEAR shows poor improvement, esp. at high incidence, poor AR in infrared due to low height

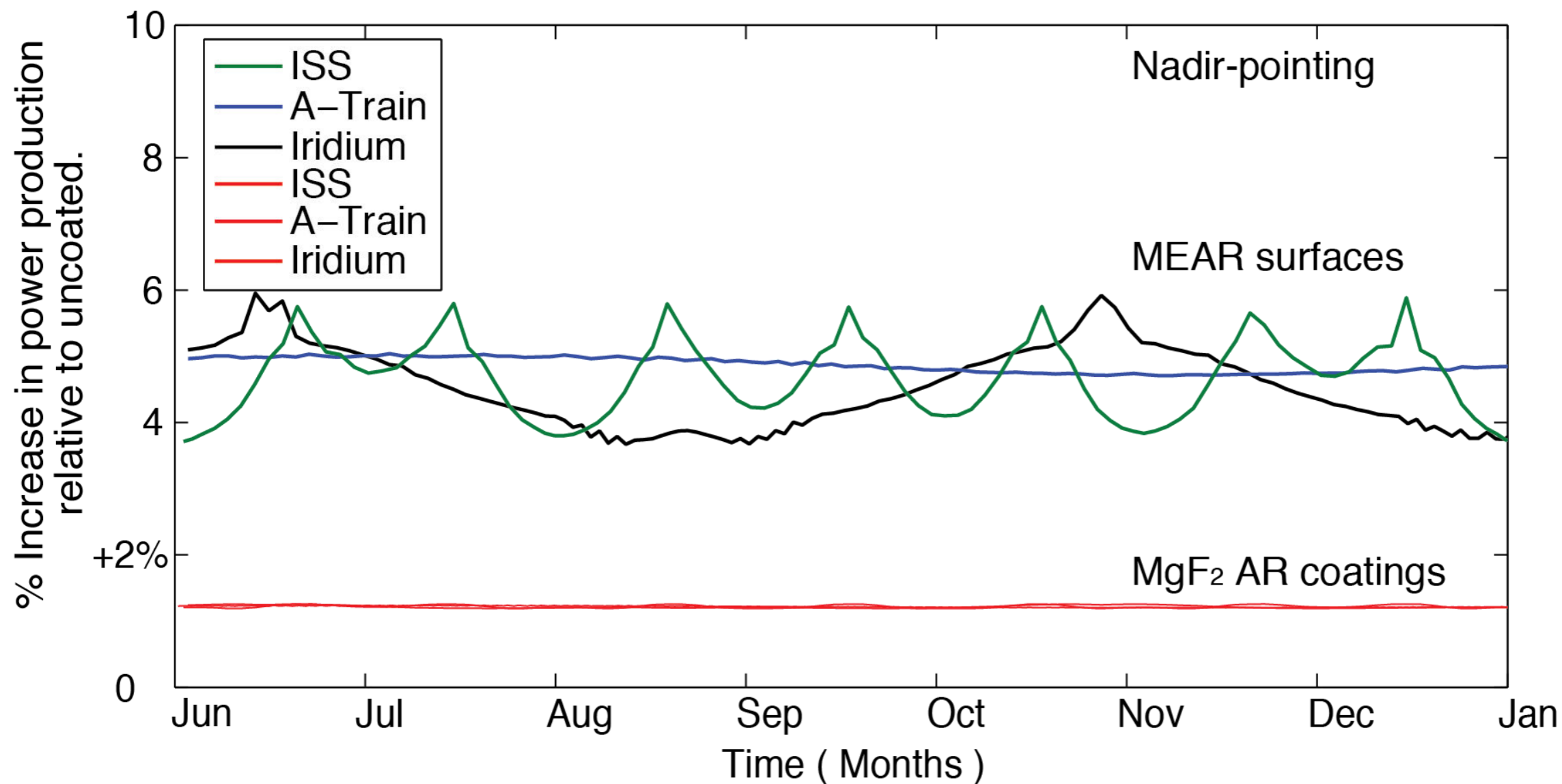


# TESTING AND CHARACTERIZATION



- 1177nm MEAR shows significant improvement at high incidence, well beyond commercial ARC

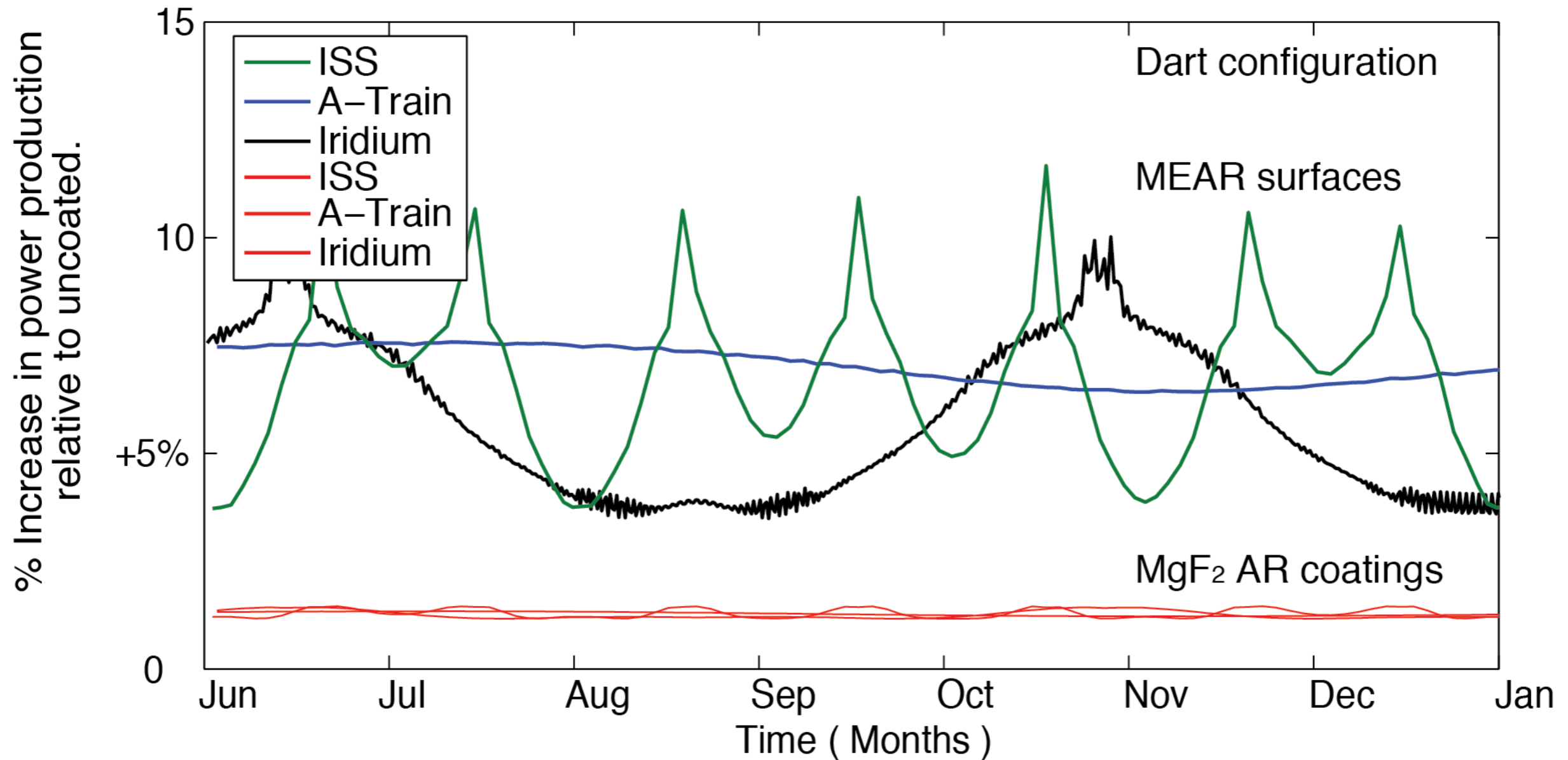
# TESTING AND CHARACTERIZATION



Orbit	Mean	Maximum	Minimum
A-Train	4.9%	5.0%	4.7%
Iridium	4.5%	6.0%	3.7%
ISS	4.6%	5.9%	3.7%
A-Train (MgF <sub>2</sub> )	1.2%	1.2%	1.2%
Iridium (MgF <sub>2</sub> )	1.2%	1.3%	1.2%
ISS (MgF <sub>2</sub> )	1.2%	1.3%	1.2%

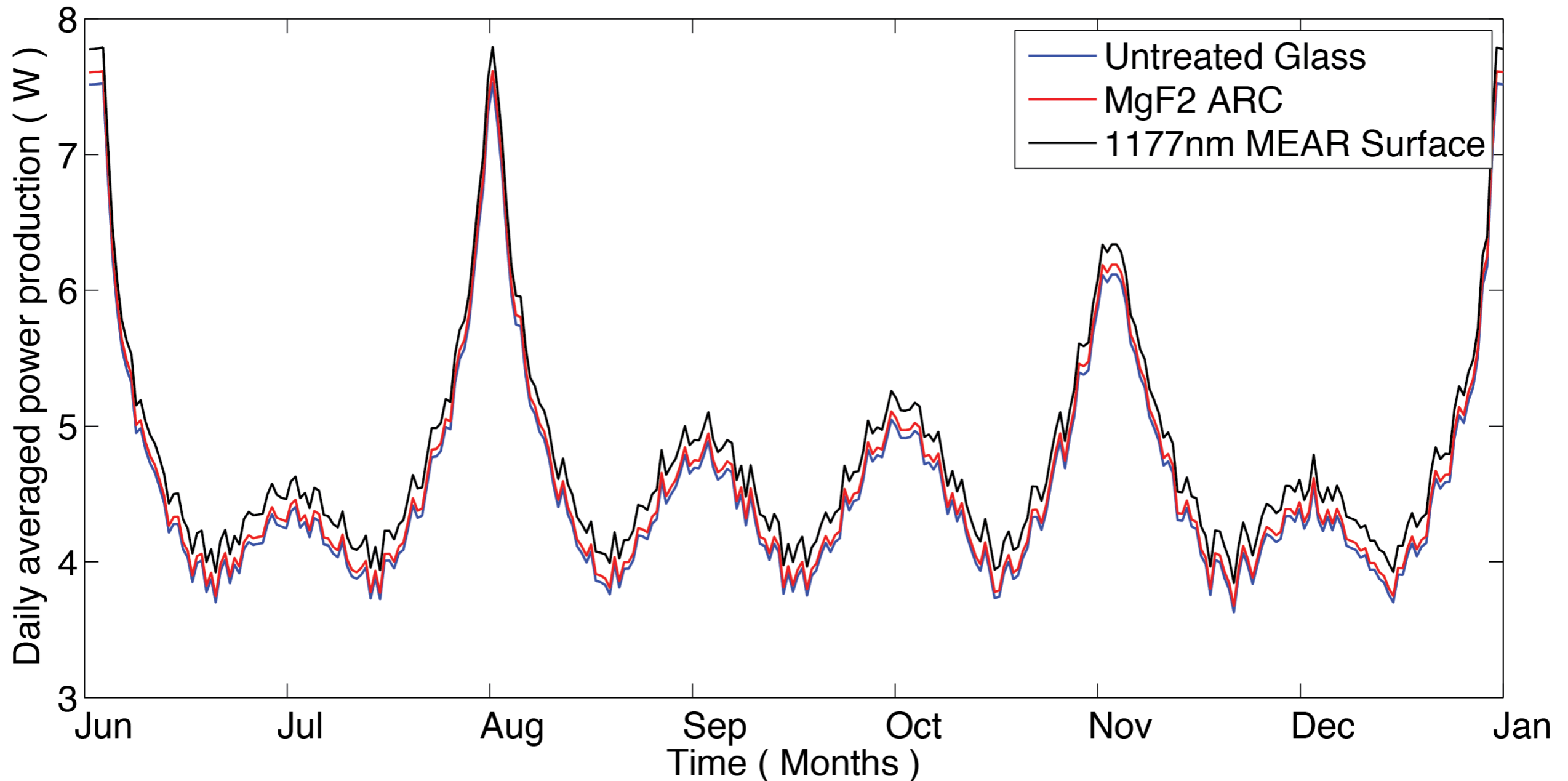


# TESTING AND CHARACTERIZATION



Orbit	Mean	Maximum	Minimum
A-Train	7.0%	7.6%	6.4%
Iridium	5.5%	9.4%	3.7%
ISS	6.5%	11.7%	3.7%
A-Train (MgF <sub>2</sub> )	1.3%	1.3%	1.2%
Iridium (MgF <sub>2</sub> )	1.2%	1.4%	1.2%
ISS (MgF <sub>2</sub> )	1.3%	1.5%	1.2%

# TESTING AND CHARACTERIZATION



- Equivalent to an extra 3.5-4.0W h / day
- Effect is enhanced during low-illumination



# RESULTS

Orbit	Mean	Maximum	Minimum
<b>1177nm MEAR Surfaces</b>			
A-Train	4.9%	5.0%	4.7%
Iridium	4.5%	6.0%	3.7%
ISS	4.6%	5.9%	3.7%
A-Train - DART	7.0%	7.6%	6.4%
Iridium - DART	5.5%	9.4%	3.7%
ISS - DART	6.5%	11.7%	3.7%
<b>MgF<sub>2</sub> AR Coatings</b>			
A-Train	1.2%	1.2%	1.2%
Iridium	1.2%	1.3%	1.2%
ISS	1.2%	1.3%	1.2%
A-Train – DART	1.3%	1.3%	1.2%
Iridium – DART	1.2%	1.4%	1.2%
ISS – DART	1.3%	1.5%	1.2%

- 3.5-4.0W h / day
- Effect enhanced during low light
- MEAR surfaces realized in single step fabrication

# SUMMARY & CONCLUSIONS

- MEAR Surfaces for CubeSats designed using RCWA.
  - Ideal height found to be 1204.1nm, pitch <150nm
- MEAR Surfaces fabricated by NSL and single-step “grass growth”
- MEAR Surfaces characterized in solar simulation environment
- Average expected power increase on orbit 4.7% for Nadir pointing, 6.3% for Dart.
  - Equivalent to increasing base cell efficiency 28.3% → 30.1%



# FUTURE WORK

- Adapt fabrication procedure for CMO glass
  - MEAR effect is geometry based, similar AR expected
- Continue to investigate the effect of applying MEAR surface to rear of coverglass
- Design 1-U test panel to fly as hosted payload
- Investigate applications to micro-rovers

# ACKNOWLEDGEMENTS

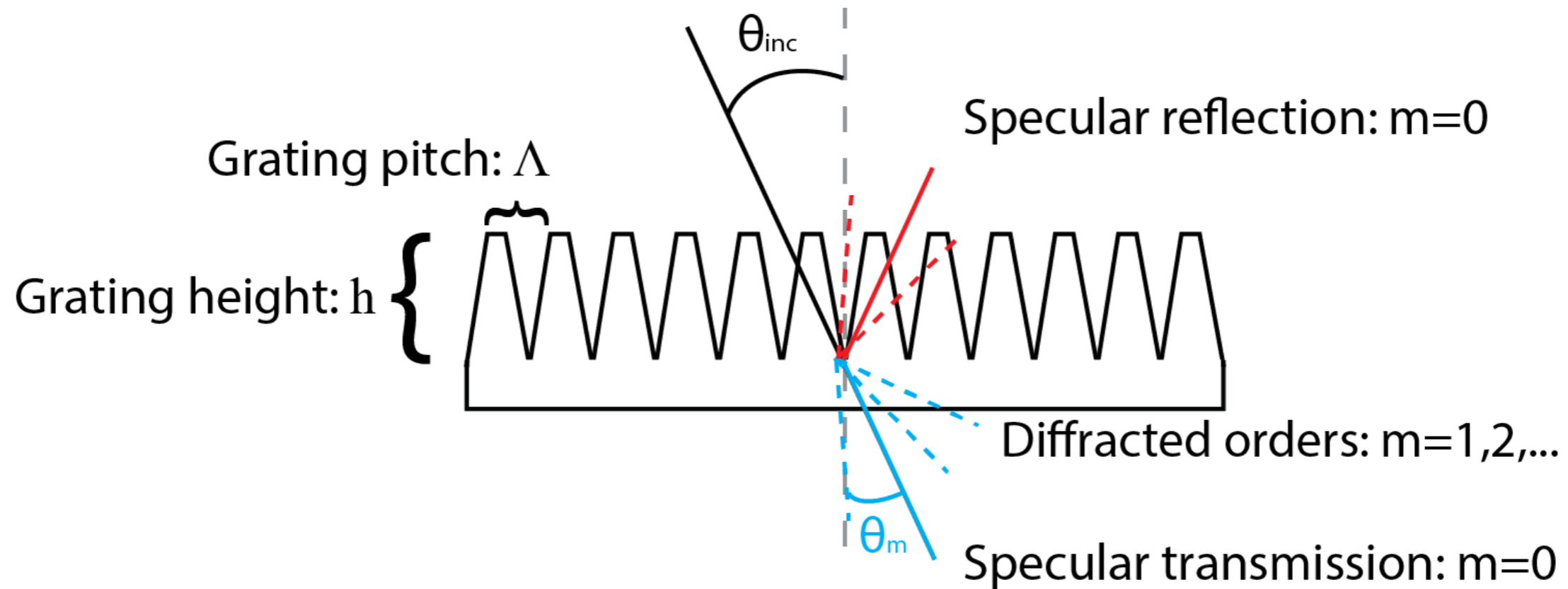


- Research assistant & microfabrication trainee  
Juan Guzman



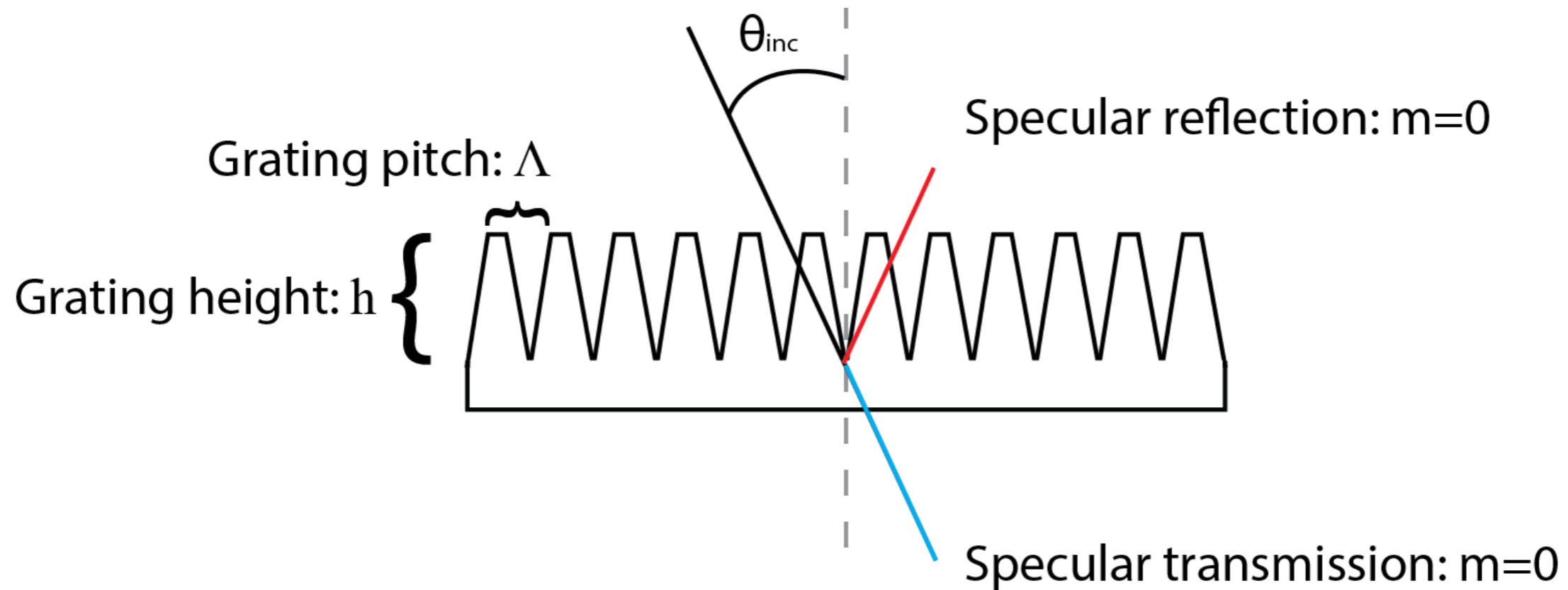


# SUPPLEMENTAL: MEAR THEORY



$$\theta_m = \arcsin \left( m \frac{\lambda}{n\Lambda} - \sin(\theta_i) \right)$$

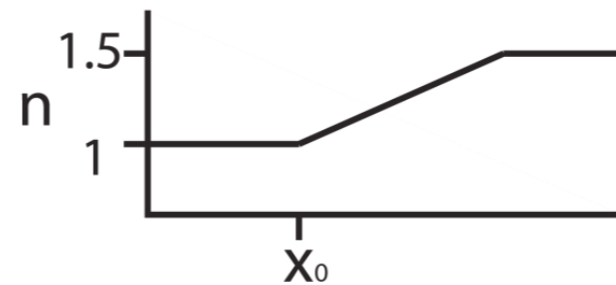
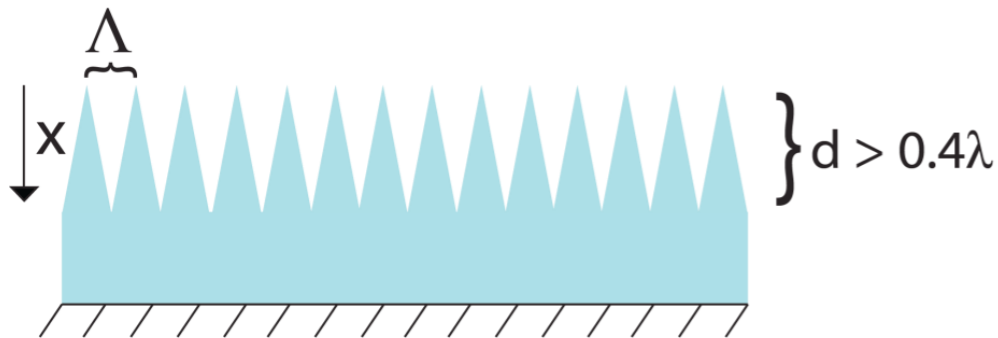
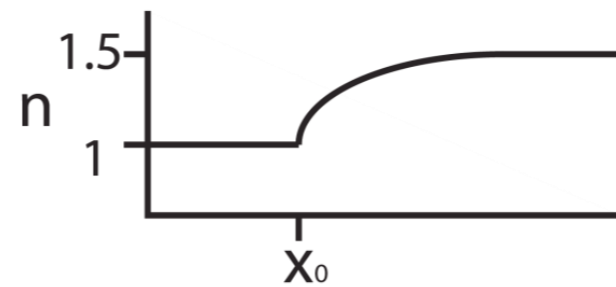
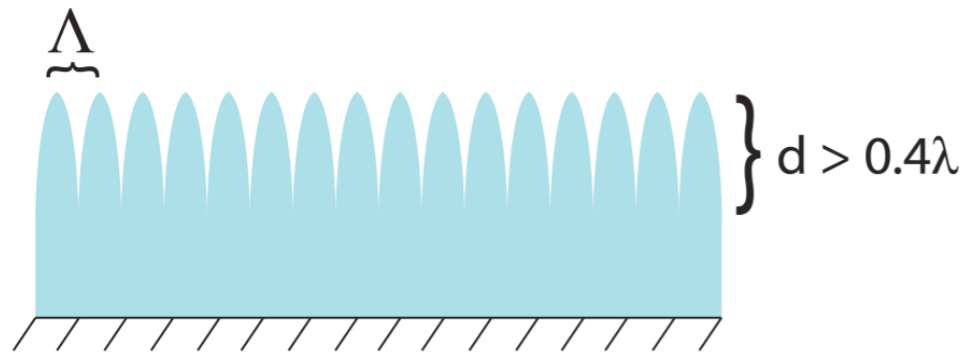
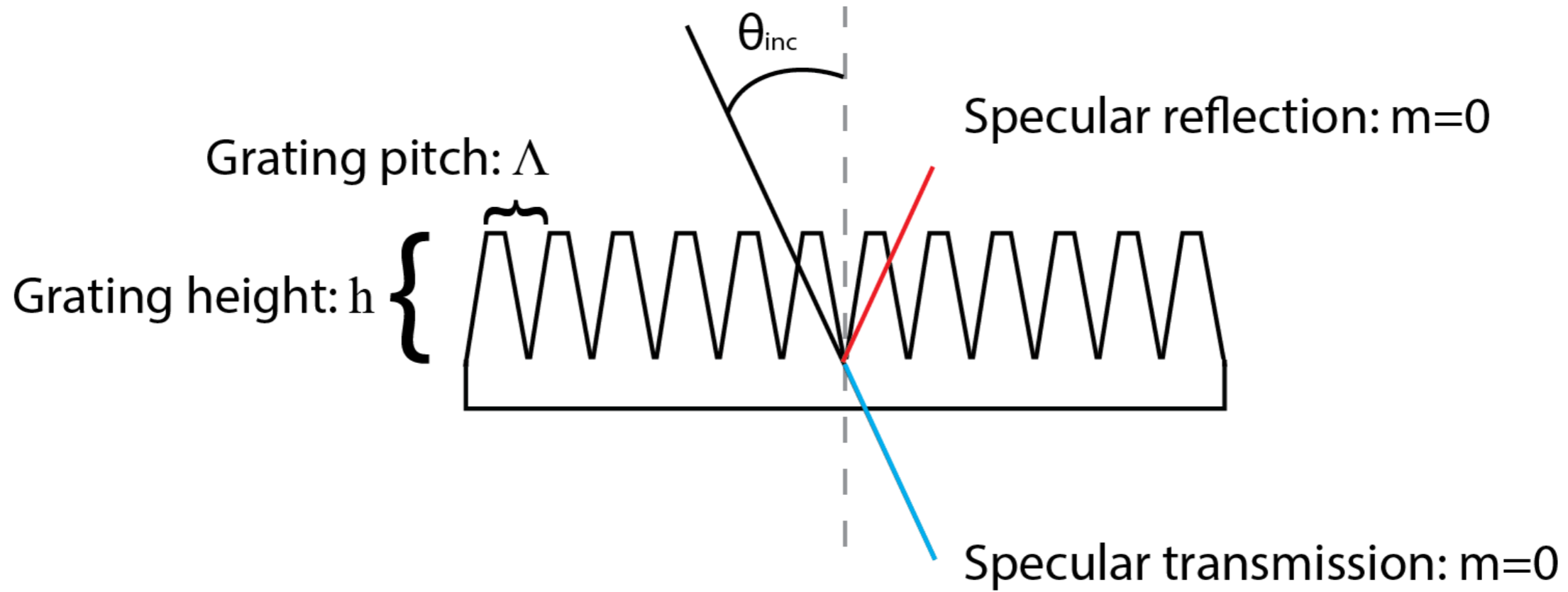
# SUPPLEMENTAL: MEAR THEORY



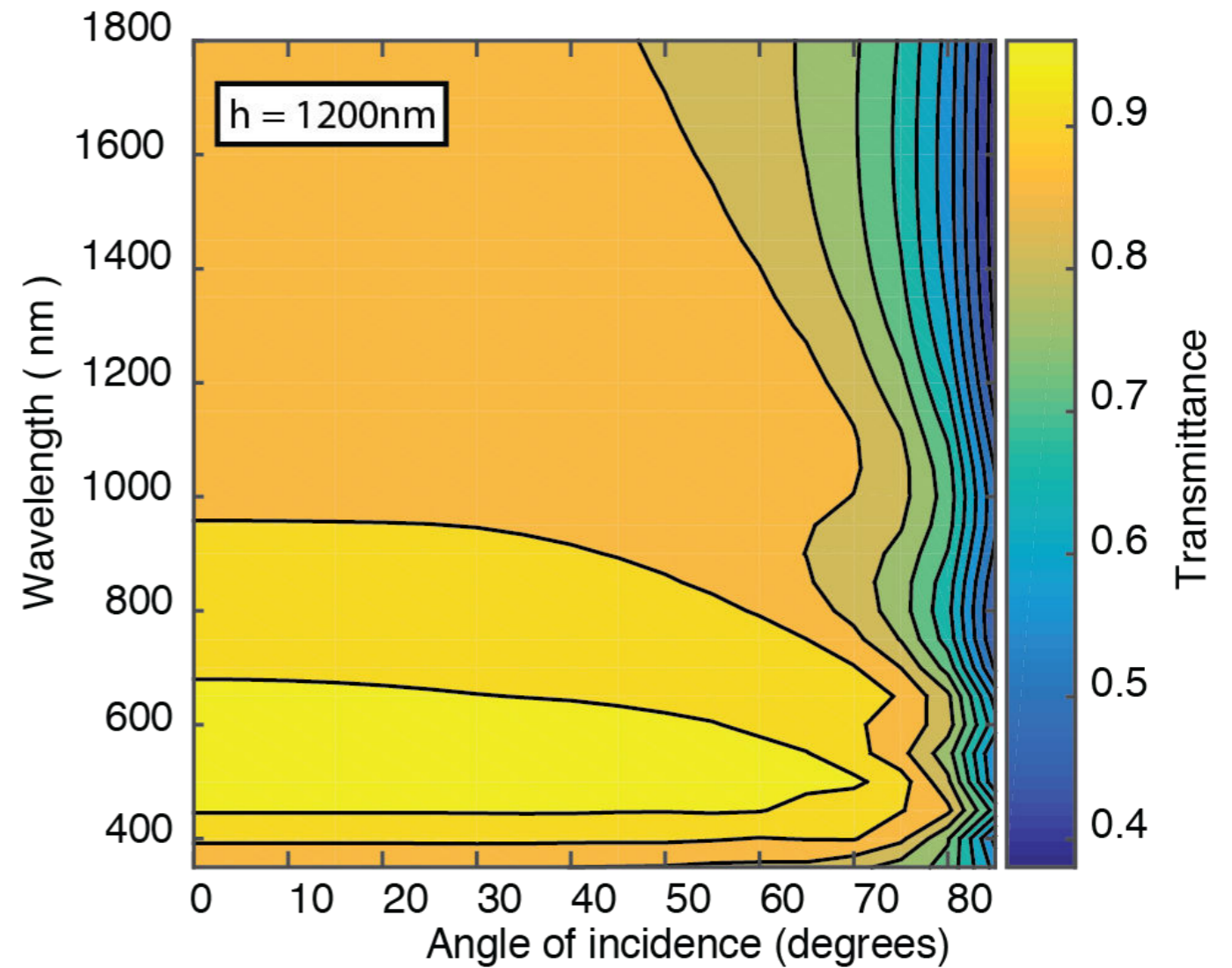
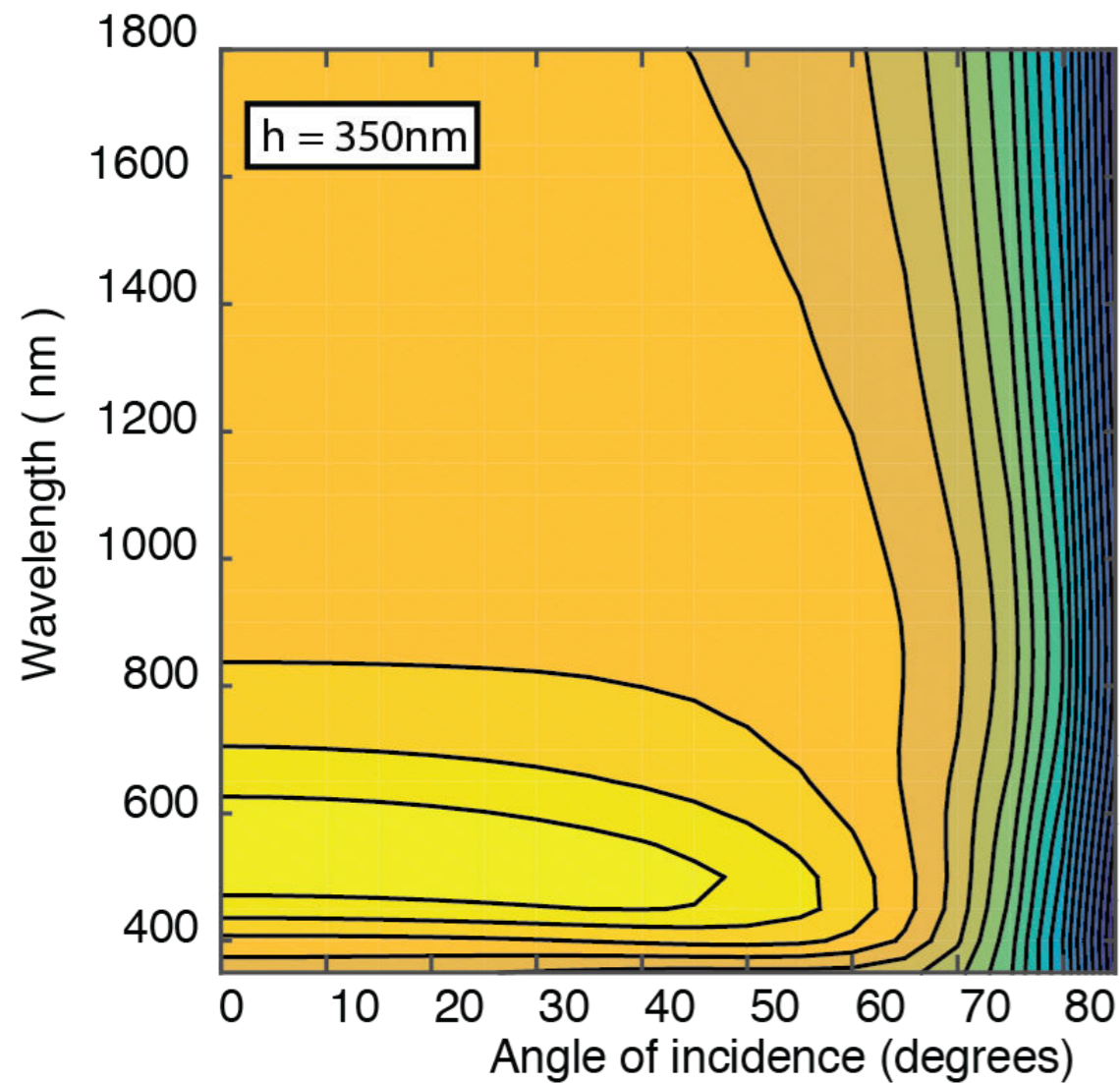
$$\theta_m = \arcsin \left( m \frac{\lambda}{n\Lambda} - \sin(\theta_i) \right)$$



# SUPPLEMENTAL: MEAR THEORY



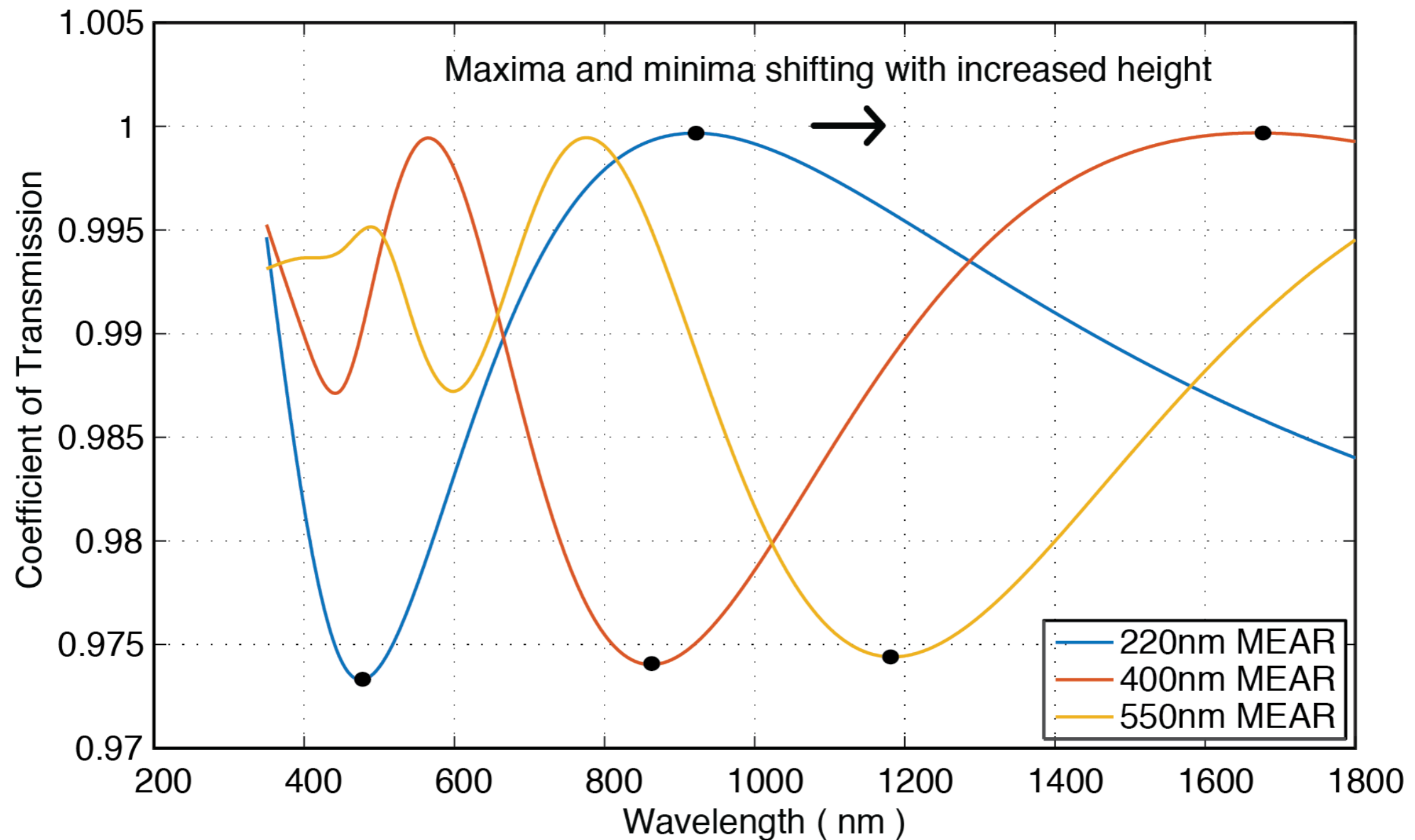
# SUPPLEMENTAL: MOTH EYE DESIGN



- Height is most “free” parameter
- Pitch is limited by subwavelength condition

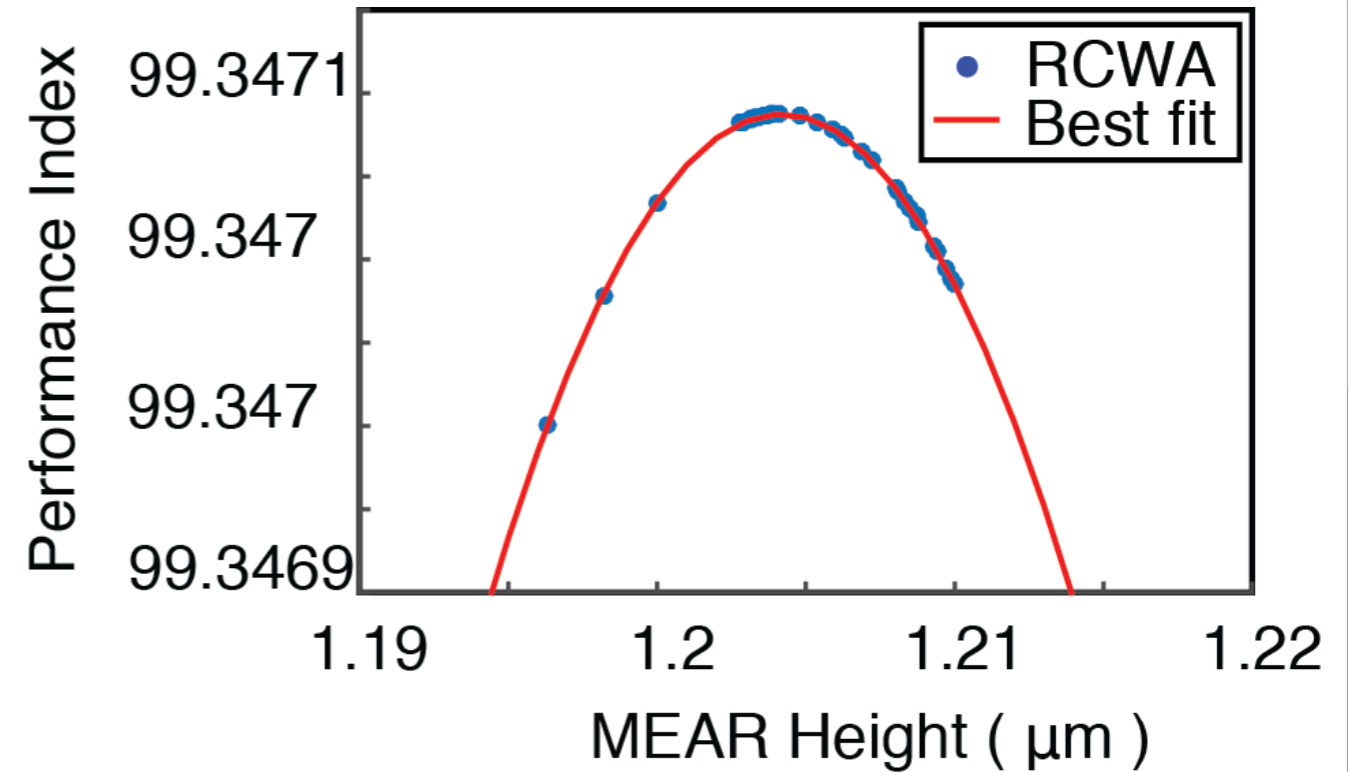
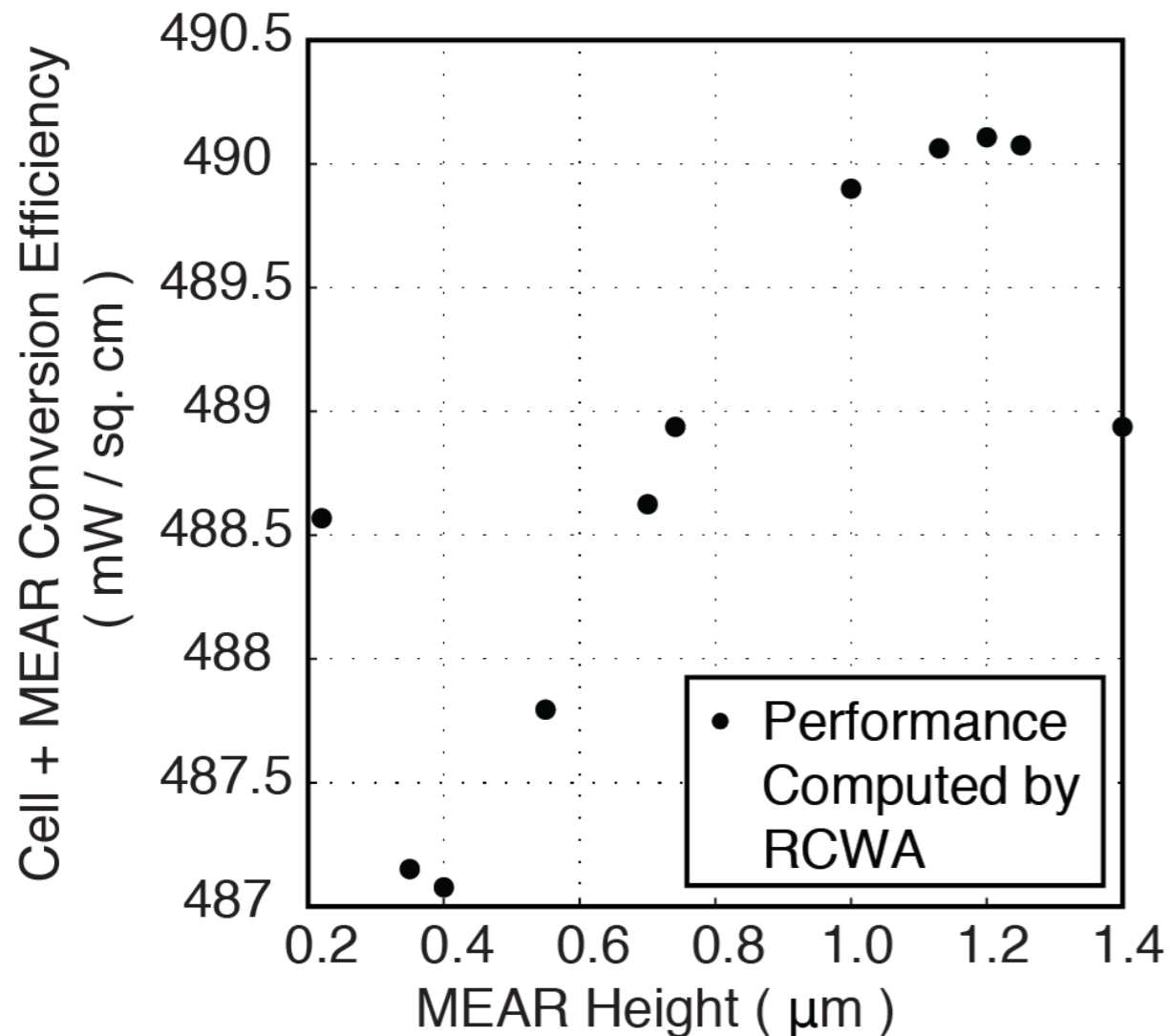


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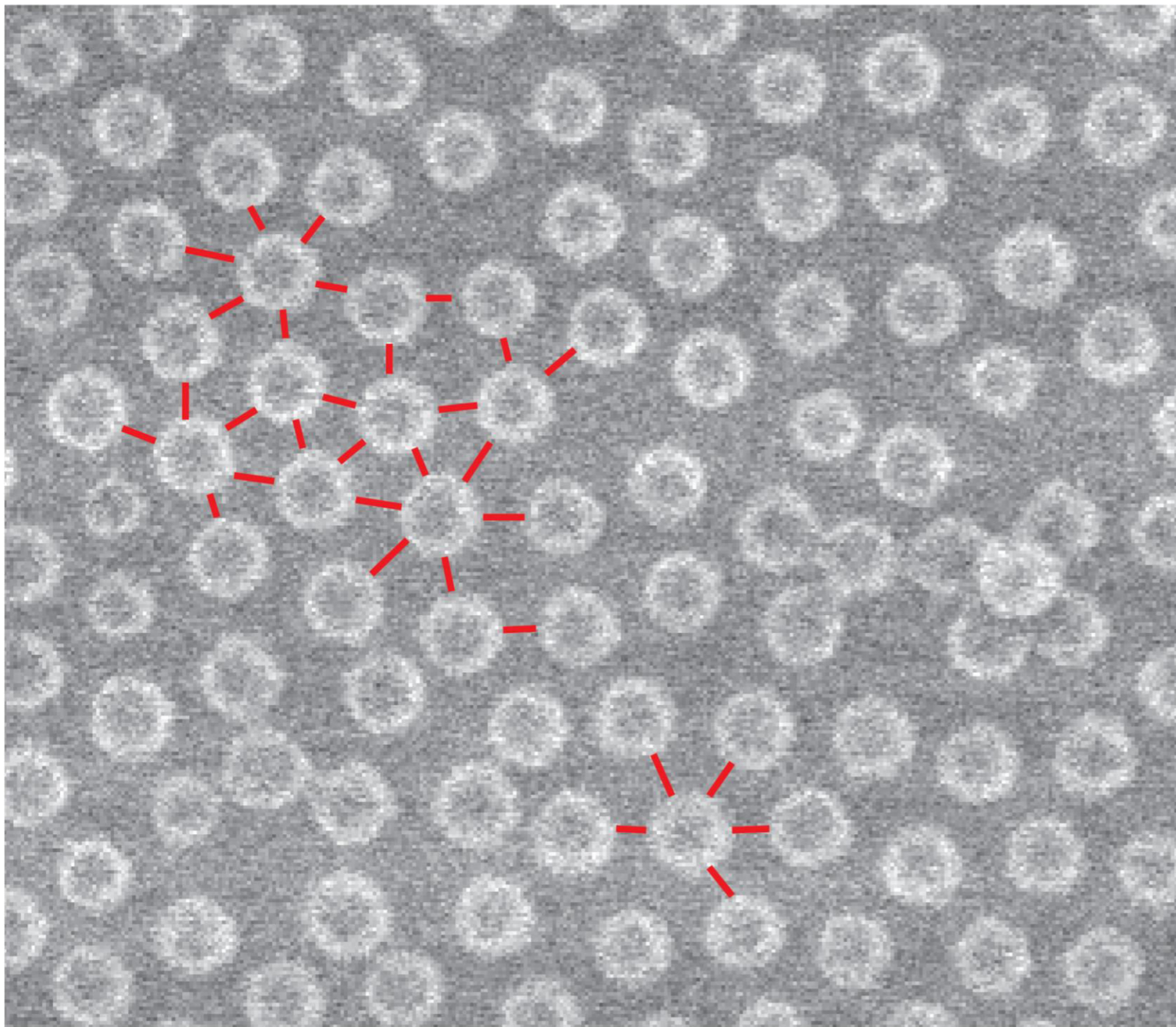
- Height is most “free” parameter
- Pitch is limited by subwavelength condition

- $h = 1204.1 \text{ nm} \pm 15.1 \text{ nm}$
- Constrained to 130nm pitch



# SUPPLEMENTAL: SIZE REDUCTION

- O<sub>2</sub> etch yields etch rate of ~60nm/min.

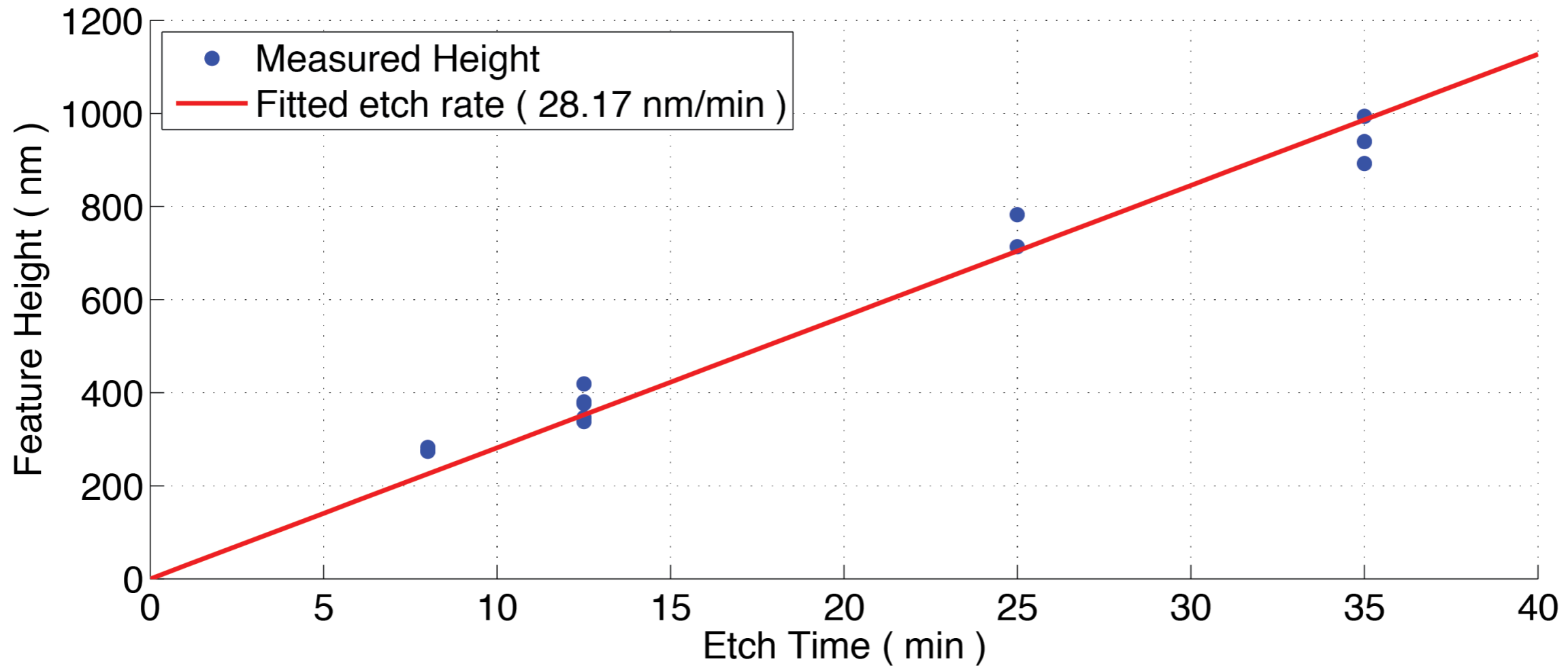


1  $\mu\text{m}$

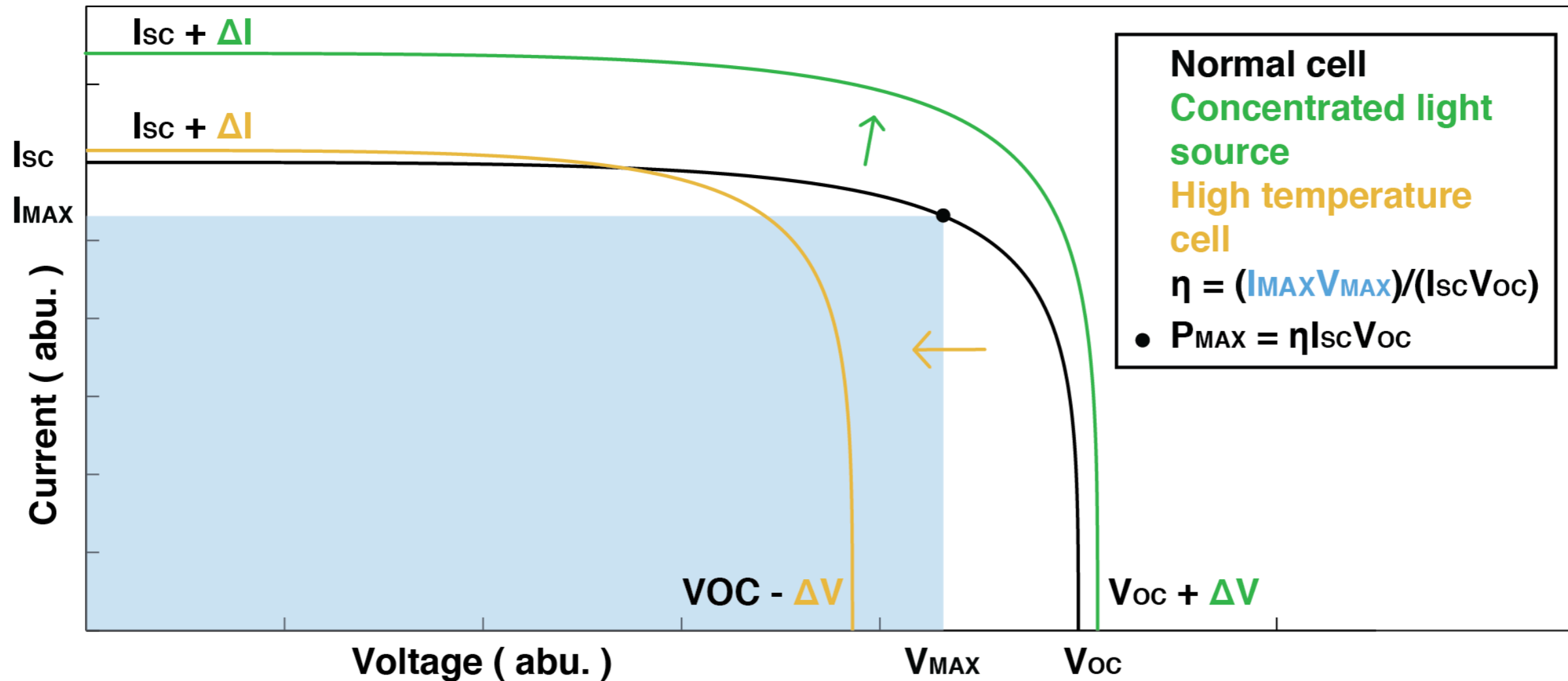
Quanta 3D FEG

# SUPPLMENTAL: ETCH RATE

Structure Height vs. Etch Time.

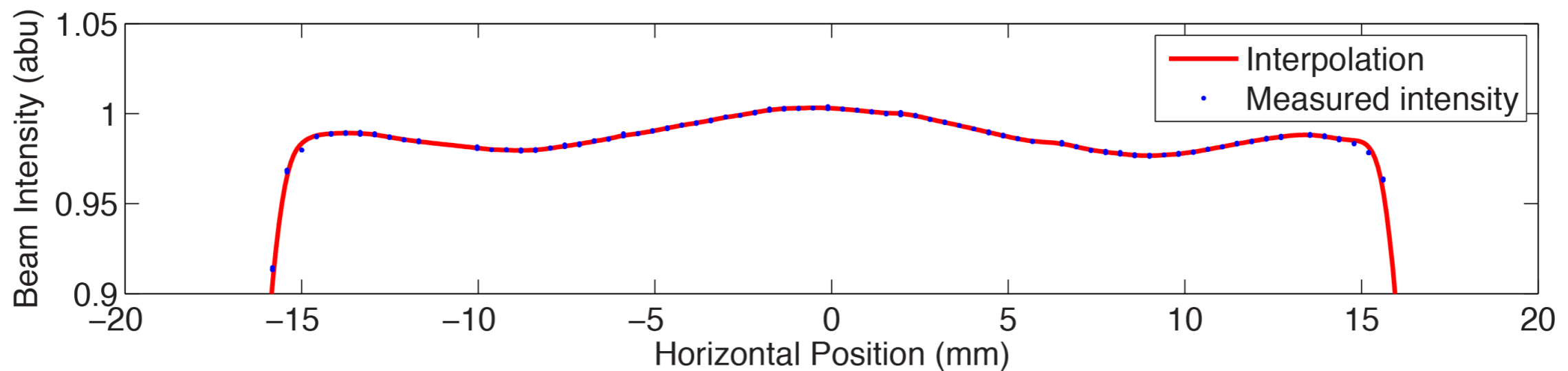
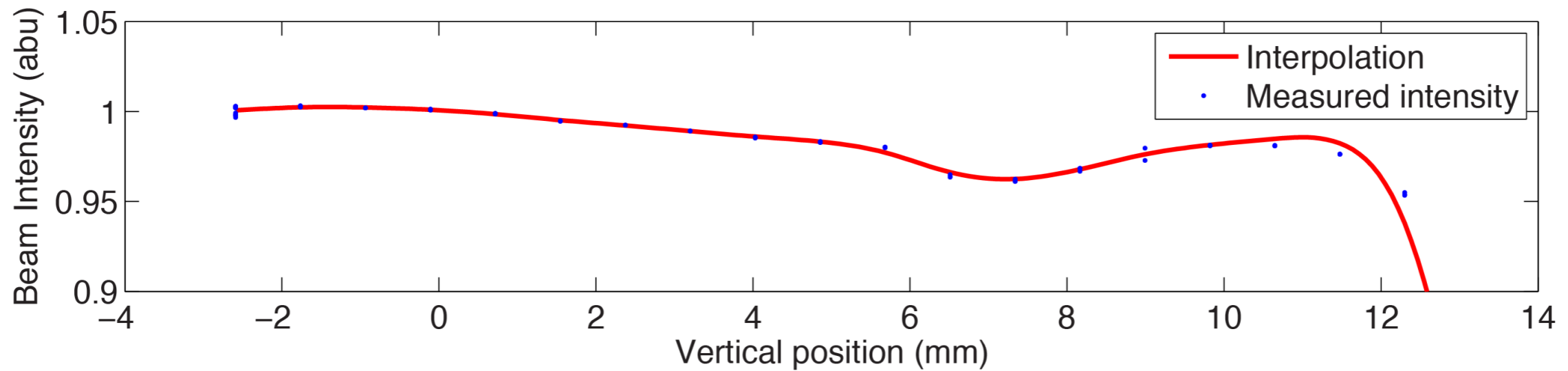


# SUPPLEMENTAL: MEASUREMENT RATIONALE

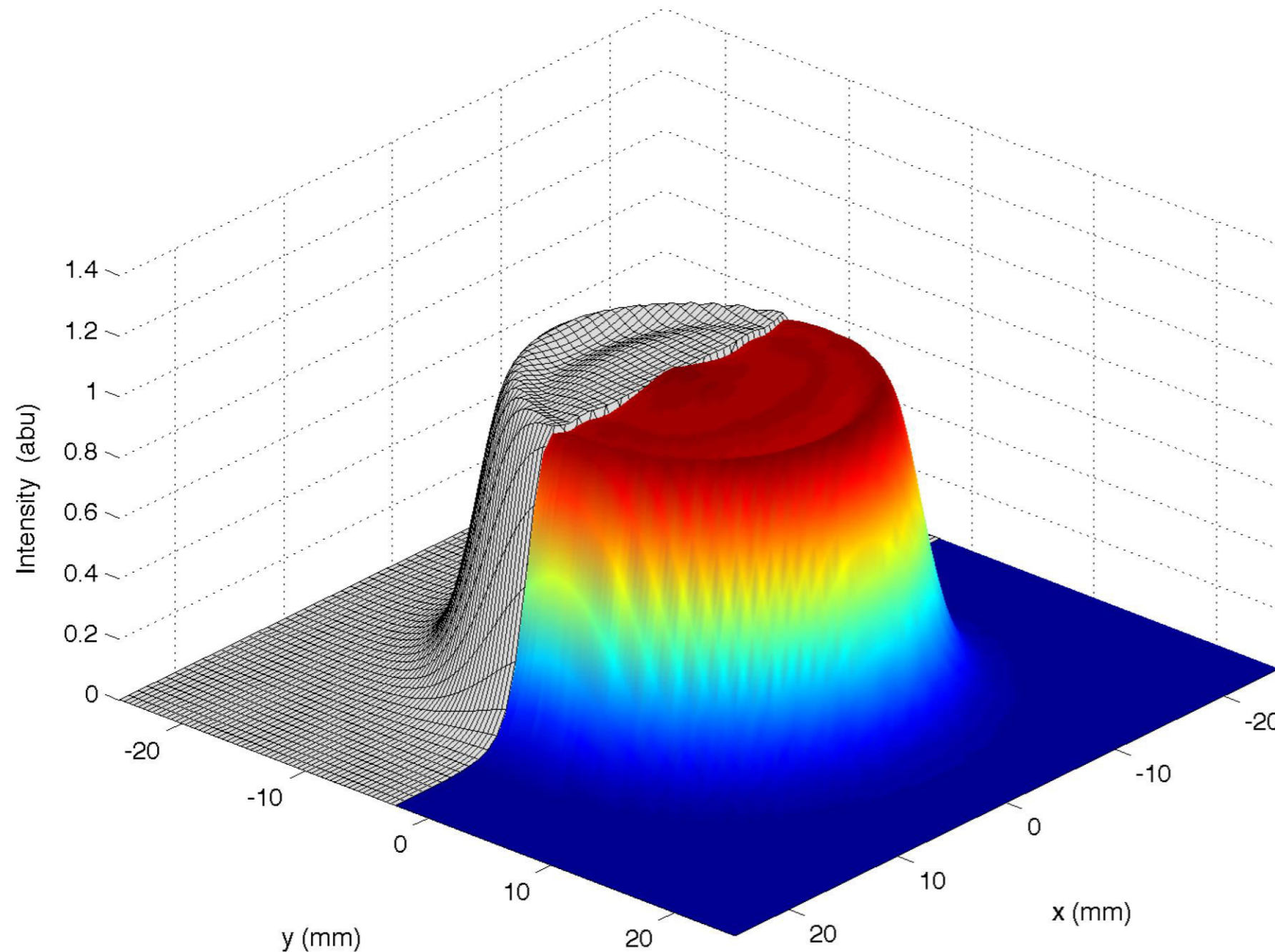




# SUPPLEMENTAL: BEAM CHARACTERIZATION

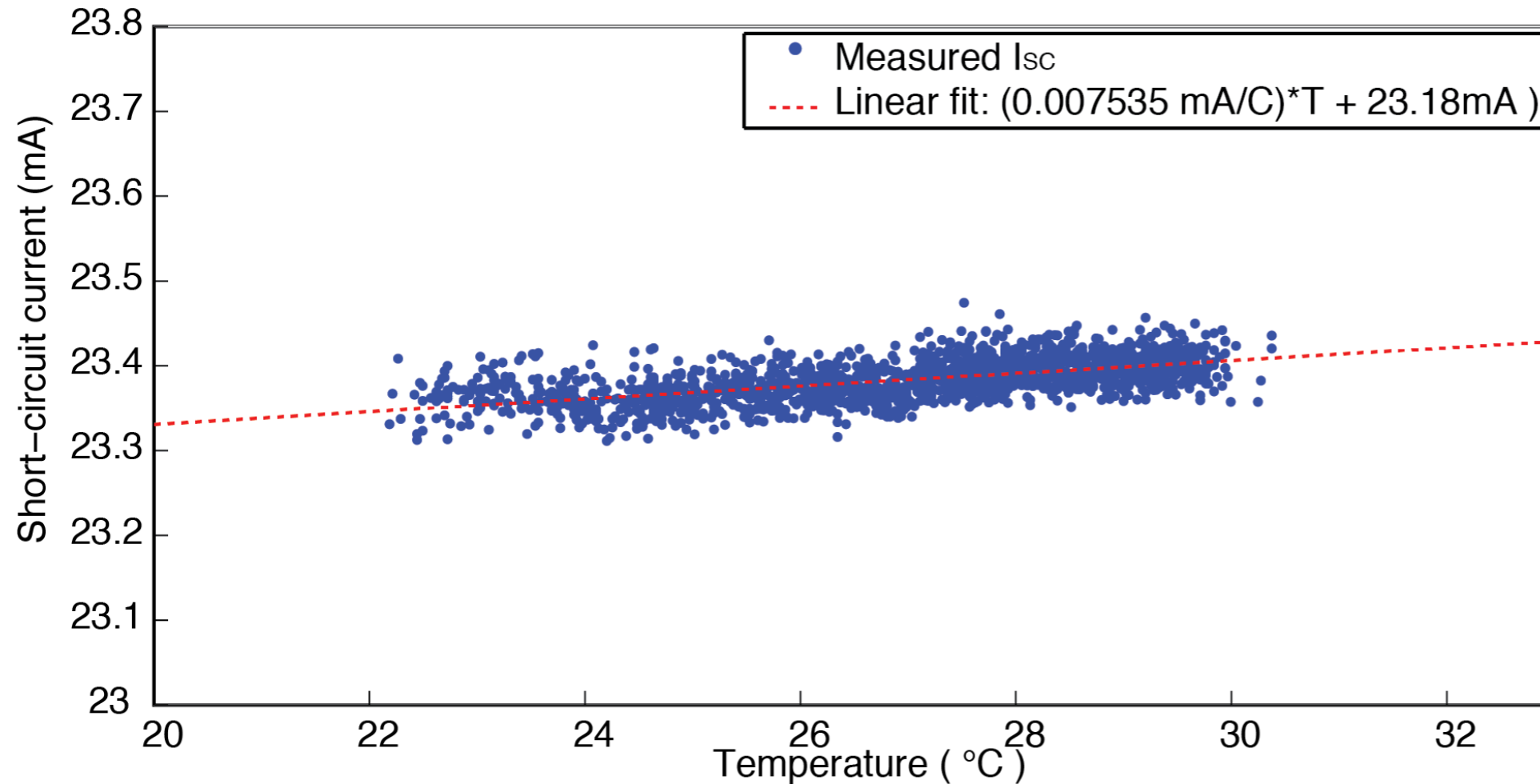


# SUPPLEMENTAL: BEAM CHARACTERIZATION



- Beam profile smooth.
- Appears as an extended Airy disk.
- Cells are not positioned below 3mm mark.

# SUPPLEMENTAL: TEMPERATURE

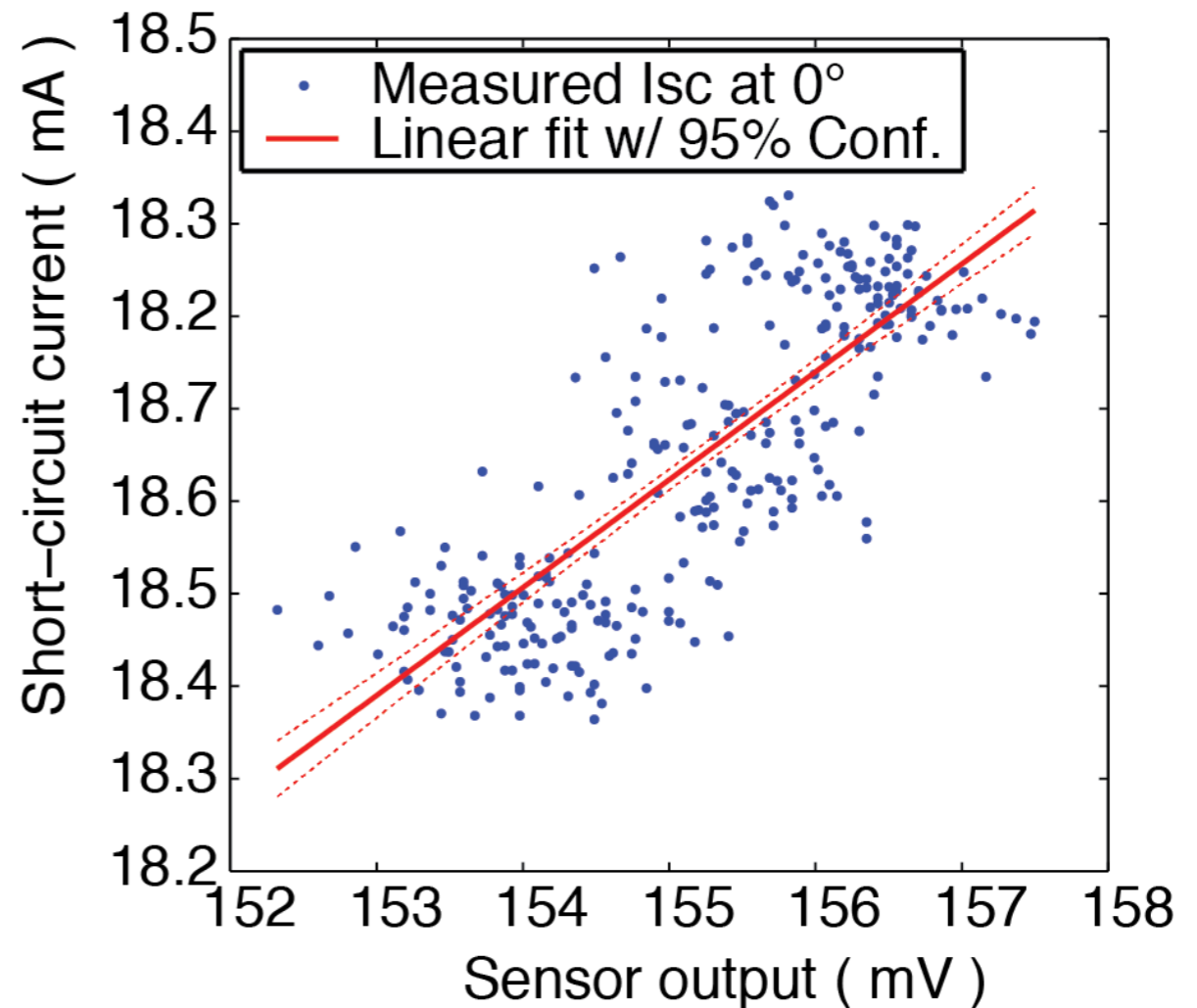
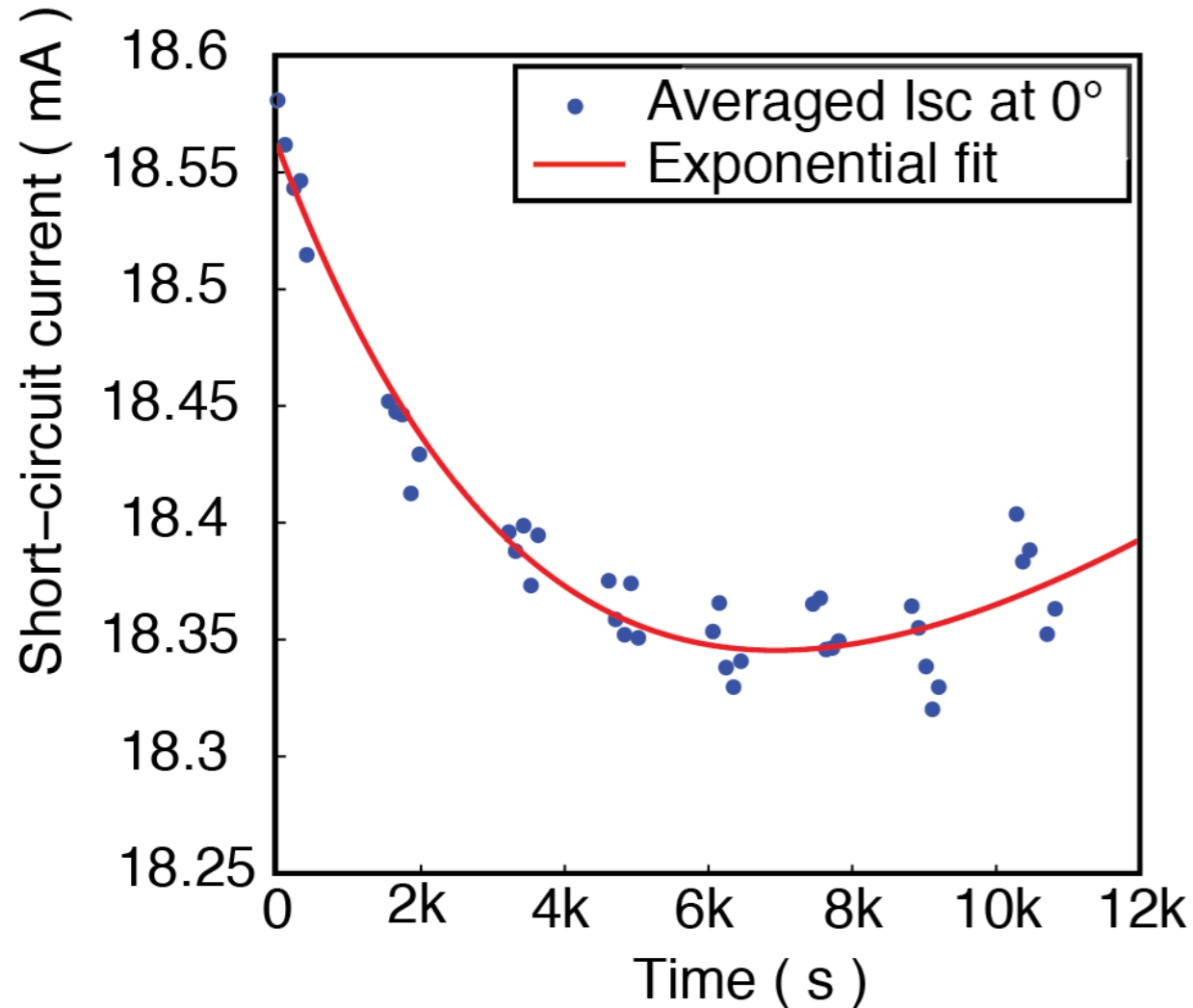


5m exposure  
~0.3% I<sub>sc</sub> shift

- Very low temperature response in I<sub>sc</sub>, V<sub>oc</sub> a different matter.
- Relative measurements → identical electrical heating

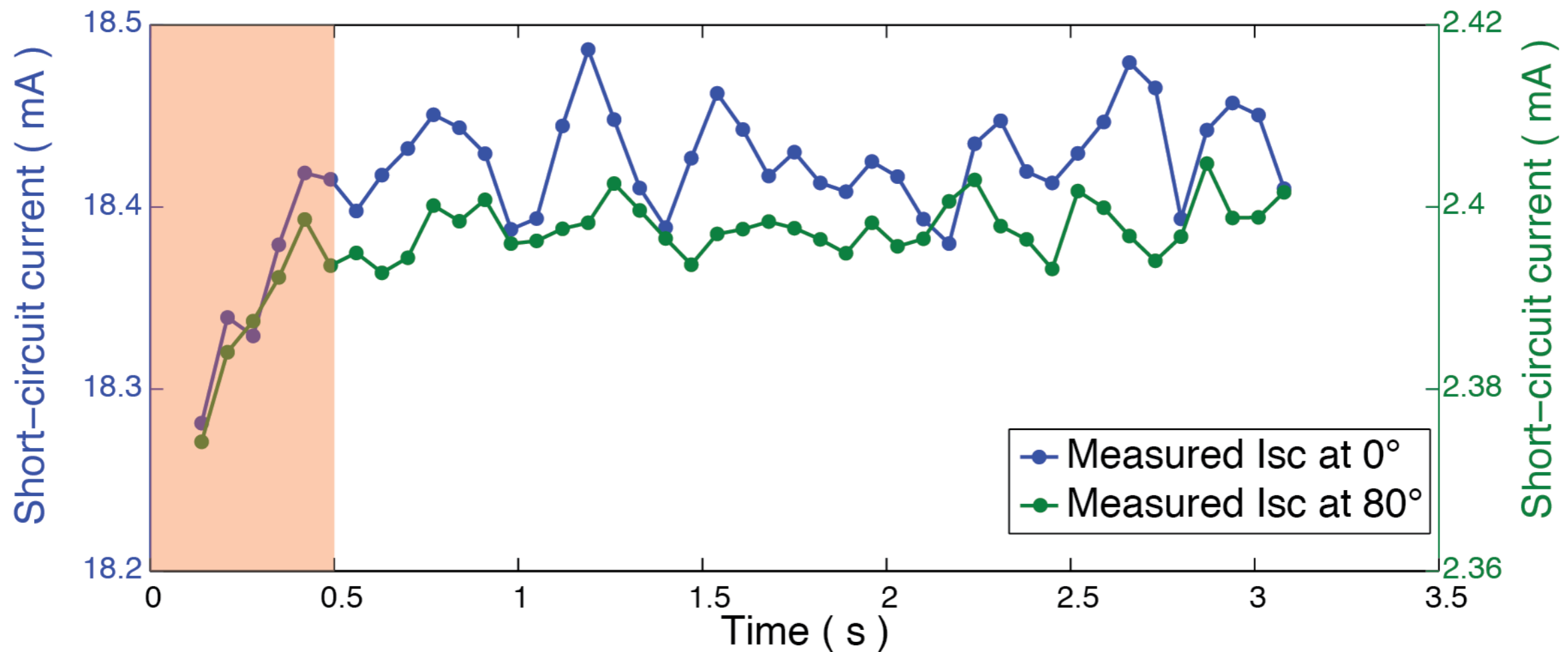


# SUPPLEMENTAL: DRIFT



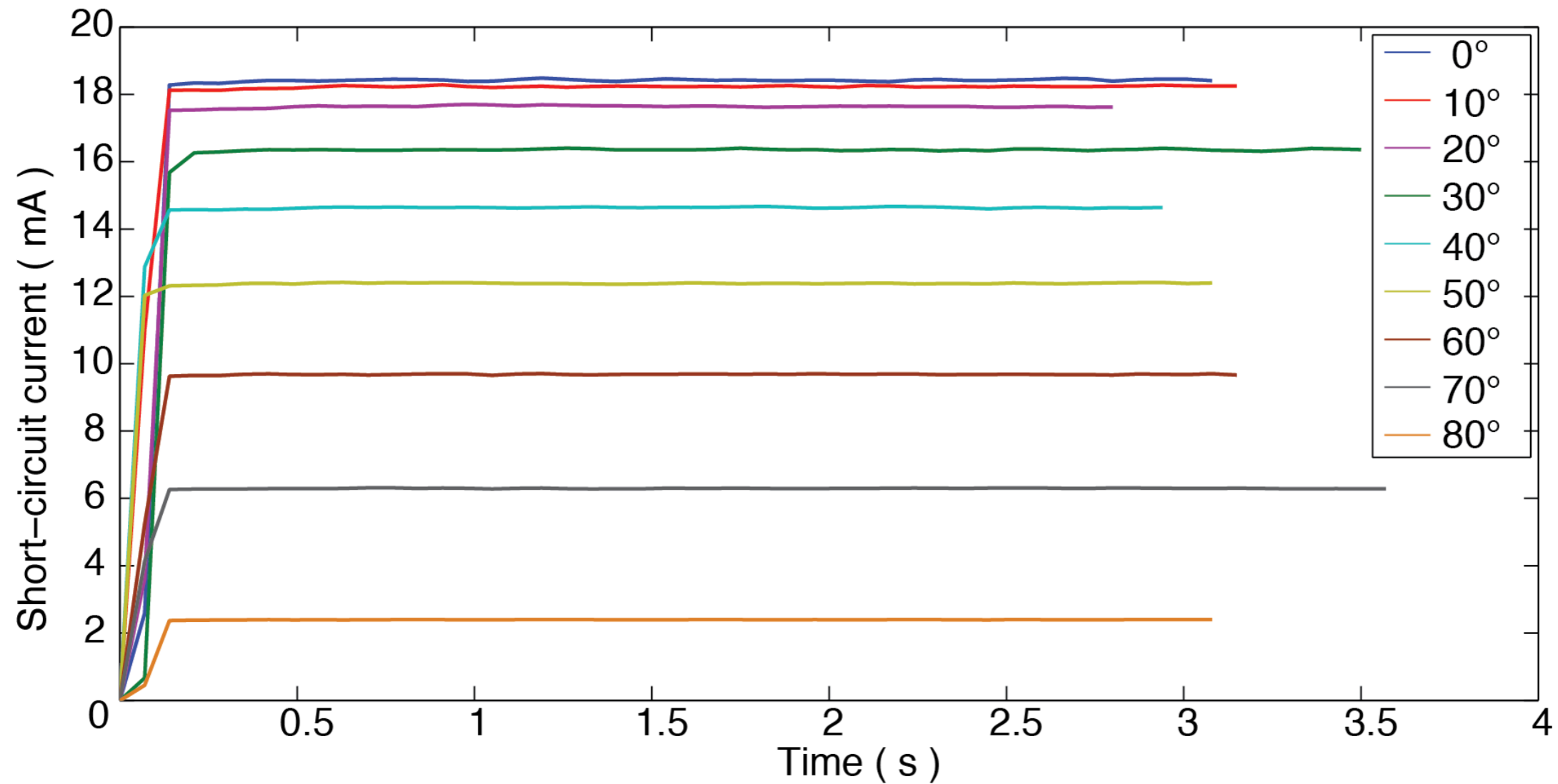
- Beam drift immediately following ignition
- May be accounted for by linear relationship with photodiode

# SUPPLEMENTAL: RC-LAG



- RC-Lag in the circuit
- 5% of final value
- First 0.5s of signal following crossover

# SUPPLEMENTAL: RC-LAG



- RC-component not significant.



# SUPPLEMENTAL: EXPECTED UNCERTAINTIES

Parameter	Symbol	Value ( $3\sigma$ )	Value as %
$I_{SC}$ readout	$\sigma I_{SC}$	0.00432 (mA)	< 0.385
Power sensor	$\sigma B_{\lambda}$	---	0.161
Position of cell on PCB (at $0^{\circ}$ )	$\sigma X_R$	0.1mm	0.484
Horizontal position of PCB (at $0^{\circ}$ )	$\sigma X_0$	0.1mm	0.489
Vertical position of PCB (at $0^{\circ}$ )	$\sigma Y_0$	0.1mm	0.006
Incident angle (at $0^{\circ}$ )	$\sigma \theta_0$	1.25 arcmin	0.00002
Position of cell on PCB (at $85^{\circ}$ )	$\sigma X_R$	0.1mm	0.004
Horizontal position of PCB (at $85^{\circ}$ )	$\sigma X_0$	0.1mm	0.036
Vertical position of PCB (at $85^{\circ}$ )	$\sigma Y_0$	0.1mm	0.006
Incident angle (at $85^{\circ}$ )	$\sigma \theta_0$	1.25 arcmin	0.832
<b>Total uncertainty in relative Transmission (<math>T_1/T_2</math>)</b>	<b><math>\sigma_T</math></b>	<b>&lt; 0.021</b>	<b>---</b>